STIC Search Report
EIC 1700

USPTO

STIC Database Tracking Number: 188657

TO: Amanda Walke
Location: REM 9C11
Art Unit : 1752
May 4, 2006

Case Serial Number: 10/800133

From: Usha Shrestha
Location: EIC 1700
REMSEN 4B28
Phone: 571/272-3519
usha.shrestha@uspto.gov

Search Notes

Examiner Walke,

As per your search request for the Case Number 10/800,133 Claim 17, the applicant's compound is not indexed as the resin structure of Claim 17 in CAS Registry file instead it is indexed as starting compound. So to complete this search I used the Registry Number of starting compound and the Ring Identifier (RID) of acetal resin as of Claim 17. If you have any questions please let me know. Thank you.

sira Search and Information Resources Administration

STIC Search Results Feedback Form

USPTO

EIC17000

Questions about the scope or the results of the search? Contact *the EIC searcher or contact:*

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

- *I am an examiner in Workgroup:* [ ] *Example: 1713*
- *Relevant prior art* ***found****, search results used as follows:*
  - ☐ 102 rejection
  - ☐ 103 rejection
  - ☐ Cited as being of interest.
  - ☐ Helped examiner better understand the invention.
  - ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature
  (journal articles, conference proceedings, new product announcements etc.)

- *Relevant prior art* ***not found:***
  - [ ] Results verified the lack of relevant prior art (helped determine patentability)
  - [ ] Results were not useful in determining patentability or understanding the invention

Comments:

Rush: Cynthia Kelly
SPE Signature

Access DB# 188657

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Amanda Wieker Examiner #: 75663 Date: 5/4/06
Art Unit: 1752 Phone Number 30 2-1337 Serial Number: 10/800133
Mail Box and Bldg/Room Location: REM 9C11 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.
****

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Bob Sheet Attached

Inventors (please provide full names):

Earliest Priority Filing Date:

***For Sequence Searches Only* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.**

Please search for the acetal resin as depicted in claim M (attached).
~~[illegible]~~
Thank you.

****

STAFF USE ONLY | **Type of Search** | **Vendors and cost where applicable**

10/800133 Examiner: WALKE, AMANDA GAU: 1752
Classification: 430/270.100 Inventor: MEMETEA , LIVIA, et al
Status: 71 - RESPONSE TO NON-FINAL OFFICE ACTION ENTERED AND FORWARDED TO EXAMINER
Title: DEVELOPMENT ENHANCEMENT OF RADIATION-SENSITIVE ELEMENTS

Bib Data report

Application Title: DEVELOPMENT ENHANCEMENT OF RADIATION-SENSITIVE ELEMENTS

Application Num: (in phx) 10/800133 **Filing Date:** 03/12/2004 **Effective Filing:** 03/12/2004
(Location History) (Foreign/Continuity Data)

Status: 71/RESPONSE TO NON-FINAL OFFICE ACTION ENTERED AND FORWARDED TO EXAMINER **Status Date:** 03/04/2006

Patent Number: Not Issued **Issue Date:** N/A **Date of Abandonment:** N/A
Confirmation Number: 6921 **PALM Location:**

Examiner: 75663, WALKE, AMANDA (Assignment Data) **Group Art Unit:** 1752 **Class/Subclass:** 430/270.100

State or Country: CANADA **Sheets/Drawing:** 0 **Total Claims:** 68 **Independent Claims:** 10

Inventors:

Last name, First name:	City:	Country or State:
MEMETEA, LIVIA	COQUITLAM	CANADA
JARAMILLO, JUANA	COQUITLAM	CANADA
BRADFORD, NICHOLAS	RICHMOND	CANADA

10/800133 Examiner: WALKE, AMANDA GAU: 1752
Classification: 430/270.100 Inventor: MEMETEA , LIVIA, et al
Status: 71 - RESPONSE TO NON-FINAL OFFICE ACTION ENTERED AND FORWARDED TO EXAMINER
Title: DEVELOPMENT ENHANCEMENT OF RADIATION-SENSITIVE ELEMENTS

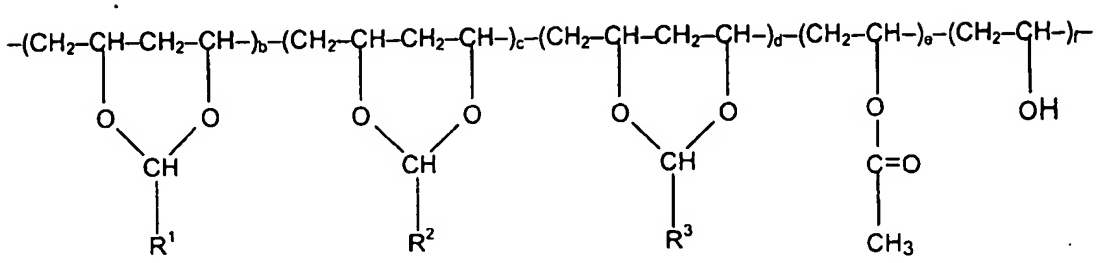
Bib Data report

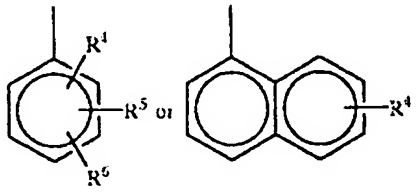
GOODIN, JONATHAN	TYLER	TEXAS
YANG, CHENG	BURNABY	CANADA
LEVANON, MOSHE	KFAR AHARON	ISRAEL

Attorneys: ALL **Attorney Docket No:** 91103/JLT

Interference No: **Lost Case:** No **Unmatched Petition:** No **L&R Code:** 1

17. The composition of claim 1, wherein the acetal resin has the structure



in which R^1 is $-C_nH_{2n+1}$ where n=1 to 12, and R^2 is 

wherein R^4 = —OH;
R^5 = —OH or $—OCH_3$ or Br— or $—O—CH_2—C\equiv CH$ and
B^6 = Br— or NO_2

R^3 = $—(CH_2)_t—COOH$, $—C\equiv CH$, or 

where R^7 = COOH, $—(CH_2)_t—COOH$, $—O—(CH_2)_t—COOH$

and in which t = 1 to 4, and where b = 5 to 40 mole %, preferably 15 to 35 mole %

c = 10 to 60 mole %, preferably 20 to 40 mole %

d = 0 to 20 mole %, preferably 0 to 10 mole %

e = 2 to 20 mole %, preferably 1 to 10 mole %

and f = 5 to 50 mole %, preferably 15 to 40 mole %.

18. A composition according to claim 17, wherein the developability-enhancing compound is at least one of

a. an alcohol having at least one of an alkyl radical of 12 - 60 carbon atoms, a fluoroalkyl radical of 4 - 60 carbon atoms and a fluoroalkylaryl radical of 7 - 60 carbon atoms;

b. a polyol;

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=> fil reg
FILE 'REGISTRY' ENTERED AT 14:47:41 ON 04 MAY 2006

=> d his

     FILE 'HCAPLUS' ENTERED AT 13:57:15 ON 04 MAY 2006
L1             1 S US20050003296/PN
               SEL RN

     FILE 'REGISTRY' ENTERED AT 13:57:36 ON 04 MAY 2006
L2            37 S E1-E37
L3           376 S 90-02-8/CRN
L4            25 S 100-83-4/CRN
L5           214 S 123-72-8/CRN
L6             1 S ETHANOL/CN
L7             1 S METHANOL/CN
L8           647 S 9002-89-5/CRN
L9             1 S 90-02-8/RN
L10            1 S 100-83-4/RN
L11            1 S 123-72-8/RN
L12            1 S 9002-89-5/RN
L13              STR
L14           50 S L13
L15        56174 S 46.248/RID
L16         1779 S L15 AND PMS/CI
L17          377 S L3 OR L4 AND L5

     FILE 'HCAPLUS' ENTERED AT 14:07:37 ON 04 MAY 2006
L18           93 S L3/DP
L19            1 S L4/DP
L20            8 S L5/DP
L21           93 S L18 OR L19 AND L20
L22            0 S (L18 OR L19) AND L20

     FILE 'REGISTRY' ENTERED AT 14:09:03 ON 04 MAY 2006
L23            2 S (L3 OR L4) AND L5

     FILE 'HCAPLUS' ENTERED AT 14:09:27 ON 04 MAY 2006
L24            1 S L23
L25          552 S L3
L26           41 S L4
L27          426 S L5
L28            3 S (L25 OR L26) AND L27
L29        11427 S L9
L30         2435 S L10
L31        12010 S L11
L32          410 S (L29 OR L30) AND L31
L33            7 S L32 AND LITHOG?
L34            4 S L32 AND RADIAT?
L35            9 S L33 OR L34
L36       191327 S L6
L37       133365 S L7
L38          217 S L9/DP
L39           18 S L10/DP
L40          111 S L11/DP
L41            5 S (L38 OR L39) AND L40
L42           14 S L24 OR L28 OR L33 OR L34 OR L35 OR L41
L43         1580 S L16
L44          131 S L43(L)COMPOSITION?
L45            2 S L44 AND LITHOG?
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L46          71 S L32 AND (L36 OR L37)
L47           0 S L46 AND PHOTOG?/SC,SX
L48           0 S L46 AND PHOTOG?
L49          13 S L46 AND DEVELOP?
L50          20 S L44 AND PHOTOG?/SC
L51          14 S L42 OR L47 OR L48
L52          20 S L45 OR L50
L53          20 S L52 NOT L51
L54        1718 S L8
L55       62669 S L12
L56           0 S L54 AND L30
L57          11 S L55 AND L30
L58           0 S L57 AND L37
L59           0 S L57 AND METHANOL
L60           8 S L57 AND PHOTOG?/SC
L61           8 S L56 OR L58 OR L59 OR L60
L62          18 S (L51 OR L61) NOT L53


=> d que l62
L3          376 SEA FILE=REGISTRY ABB=ON  PLU=ON  90-02-8/CRN
L4           25 SEA FILE=REGISTRY ABB=ON  PLU=ON  100-83-4/CRN
L5          214 SEA FILE=REGISTRY ABB=ON  PLU=ON  123-72-8/CRN
L6            1 SEA FILE=REGISTRY ABB=ON  PLU=ON  ETHANOL/CN
L7            1 SEA FILE=REGISTRY ABB=ON  PLU=ON  METHANOL/CN
L8          647 SEA FILE=REGISTRY ABB=ON  PLU=ON  9002-89-5/CRN
L9            1 SEA FILE=REGISTRY ABB=ON  PLU=ON  90-02-8/RN
L10           1 SEA FILE=REGISTRY ABB=ON  PLU=ON  100-83-4/RN
L11           1 SEA FILE=REGISTRY ABB=ON  PLU=ON  123-72-8/RN
L12           1 SEA FILE=REGISTRY ABB=ON  PLU=ON  9002-89-5/RN
L15       56174 SEA FILE=REGISTRY ABB=ON  PLU=ON  46.248/RID
L16        1779 SEA FILE=REGISTRY ABB=ON  PLU=ON  L15 AND PMS/CI
L23           2 SEA FILE=REGISTRY ABB=ON  PLU=ON  (L3 OR L4) AND L5
L24           1 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L23
L25         552 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L3
L26          41 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L4
L27         426 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L5
L28           3 SEA FILE=HCAPLUS ABB=ON   PLU=ON  (L25 OR L26) AND L27
L29       11427 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L9
L30        2435 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L10
L31       12010 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L11
L32         410 SEA FILE=HCAPLUS ABB=ON   PLU=ON  (L29 OR L30) AND L31
L33           7 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L32 AND LITHOG?
L34           4 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L32 AND RADIAT?
L35           9 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L33 OR L34
L36      191327 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L6
L37      133365 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L7
L38         217 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L9/DP
L39          18 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L10/DP
L40         111 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L11/DP
L41           5 SEA FILE=HCAPLUS ABB=ON   PLU=ON  (L38 OR L39) AND L40
L42          14 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L24 OR L28 OR L33 OR
                L34 OR L35 OR L41
L43        1580 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L16
L44         131 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L43(L)COMPOSITION?
L45           2 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L44 AND LITHOG?
L46          71 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L32 AND (L36 OR L37)
L47           0 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L46 AND PHOTOG?/SC,SX

L48           0 SEA FILE=HCAPLUS ABB=ON   PLU=ON  L46 AND PHOTOG?
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L50          20 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L44 AND PHOTOG?/SC
L51          14 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L42 OR L47 OR L48
L52          20 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L45 OR L50
L53          20 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L52 NOT L51
L54        1718 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L8
L55       62669 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L12
L56           0 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L54 AND L30
L57          11 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L55 AND L30
L58           0 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L57 AND L37
L59           0 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L57 AND METHANOL
L60           8 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L57 AND PHOTOG?/SC
L61           8 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L56 OR L58 OR L59 OR
                L60
L62          18 SEA FILE=HCAPLUS ABB=ON  PLU=ON  (L51 OR L61) NOT L53

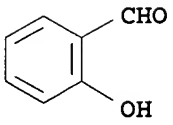

=> fil hcap
FILE 'HCAPLUS' ENTERED AT 14:47:56 ON 04 MAY 2006


=> => d l62 1-18 ibib abs hitstr hitind

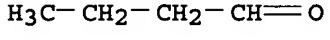
L62  ANSWER 1 OF 18  HCAPLUS  COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER:        2006:323592  HCAPLUS
TITLE:                   Positive working lithographic
                         printing plate master showing excellent
                         chemical-resistance and developablity for
                         direct platemaking by IR laser irradiation
INVENTOR(S):             Nakamura, Ippei
PATENT ASSIGNEE(S):      Fuji Photo Film Co., Ltd., Japan
SOURCE:                  Jpn. Kokai Tokkyo Koho, 50 pp.
                         CODEN: JKXXAF
DOCUMENT TYPE:           Patent
LANGUAGE:                Japanese
FAMILY ACC. NUM. COUNT:  1
PATENT INFORMATION:

     PATENT NO.           KIND   DATE        APPLICATION NO.        DATE
     ---------------      ----   --------    --------------------
     --------
     JP 2006091781         A2    20060406    JP 2004-280628
                                                                   2004
                                                                   0927
PRIORITY APPLN. INFO.:                       JP 2004-280628
                                                                   2004
                                                                   0927

AB   The title lithog. printing plate master comprises on a
     support a pos.-working recording layer containing an alkali-soluble
     polymer having a sulfonamide group and a vinyl acetal structure.
     The recording layer may include a IR absorbing agent.
IT   90-02-8D, 2-Hydroxybenzaldehyde, acetals with vinyl
     acetate-vinyl alc. copolymer 123-72-8D, Butyral, acetals
     with vinyl acetate-vinyl alc. copolymer
        (pos. working lithog. printing plate master showing
        excellent chemical-resistance and developablity for direct
        platemaking by IR laser irradiation)
RN   90-02-8  HCAPLUS
CN   Benzaldehyde, 2-hydroxy- (9CI)  (CA INDEX NAME)
```



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
ST pos working **lithog** printing plate master photoimaging material laser
IT Photoimaging materials
(photopolymerizable; pos. working **lithog.** printing plate master showing excellent chemical-resistance and developablity for direct platemaking by IR laser irradiation)
IT **Lithographic** plates
(pos. working **lithog.** printing plate master showing excellent chemical-resistance and developablity for direct platemaking by IR laser irradiation)
IT 134127-48-3
(IR dye; pos. working **lithog.** printing plate master showing excellent chemical-resistance and developablity for direct platemaking by IR laser irradiation)
IT 63-74-1D, reaction products with vinyl acetate-vinyl alc. copolymer **90-02-8D**, 2-Hydroxybenzaldehyde, acetals with vinyl acetate-vinyl alc. copolymer **123-72-8D**, Butyral, acetals with vinyl acetate-vinyl alc. copolymer 528-44-9D, 1,2,4-Benzenetricarboxylic acid, reaction products with vinyl acetate-vinyl alc. copolymer 25213-24-5D, Vinyl acetate-vinyl alcohol copolymer, acetals, aminosulfonylamides 85622-69-1D, reaction products with vinyl acetate-vinyl alc. copolymer 882045-60-5D, acetals, aminosulfonylamides
(pos. working **lithog.** printing plate master showing excellent chemical-resistance and developablity for direct platemaking by IR laser irradiation)

L62 ANSWER 2 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2006:323297 HCAPLUS
TITLE: **Lithographic** printing master plate containing polymer with cyclic structures
INVENTOR(S): Nakamura, Ippei
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 49 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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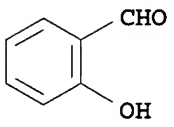
JP 2006091772 A2 20060406 JP 2004-280535
2004
0927

PRIORITY APPLN. INFO.: JP 2004-280535
2004
0927

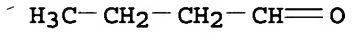
AB Disclosed is a **lithog.** printing master plate comprising on a support a pos.-working recording layer containing an alkali-soluble polymer having a maleimide-derived cyclic structure and a vinyl acetal-drived cyclic structure.

IT **90-02-8D**, 2-Hydroxybenzaldehyde, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. **123-72-8D**, Butanal, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc.
(**Lithog.** printing master plate containing polymer with cyclic structures)

RN 90-02-8 HCAPLUS
CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

ST **lithog** printing master plate polymer cyclic structure; maleimide vinyl acetal cyclic structure

IT **Lithographic** plates
(**Lithog.** printing master plate containing polymer with cyclic structures)

IT Polyvinyl acetals
(**Lithog.** printing master plate containing polymer with cyclic structures)

IT **90-02-8D**, 2-Hydroxybenzaldehyde, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. 108-05-4D, Vinyl acetate, polymers with cyclized polyvinyl acetals, phenylmaleimide, and vinyl alc. **123-72-8D**, Butanal, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. 298-12-4D, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. 557-75-5D, Vinyl alcohol, polymers with cyclized polyvinyl acetals, vinyl acetate, and phenylmaleimide 941-69-5D, N-Phenylmaleimide, polymers with cyclized polyvinyl acetals, vinyl acetate, and vinyl alc. 232610-57-0D, polymers with cyclized polyvinyl acetals, phenylmaleimide, vinyl acetate, and vinyl alc. 882045-60-5D, polymers with cyclized polyvinyl acetals, phenylmaleimide, vinyl acetate, and vinyl alc.
(**Lithog.** printing master plate containing polymer with

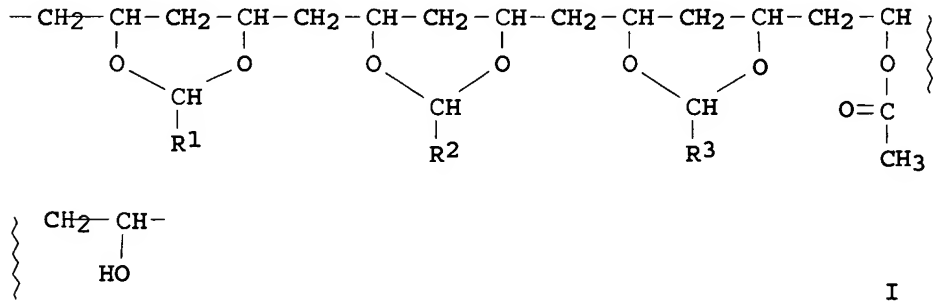
cyclic structures)

L62 ANSWER 3 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:1050639 HCAPLUS
DOCUMENT NUMBER: 143:356646
TITLE: Light-sensitive **lithographic** printing plate
INVENTOR(S): Nagashima, Akira
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: U.S. Pat. Appl. Publ., 19 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005214678	A1	20050929	US 2005-89487	2005 0325
JP 2005275231	A2	20051006	JP 2004-91362	2004 0326

PRIORITY APPLN. INFO.: JP 2004-91362 A 2004 0326

GI

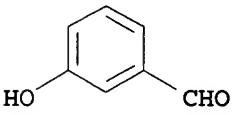


I

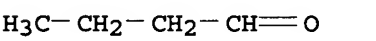
AB A light-sensitive **lithog.** printing plate comprises a hydrophilic substrate provided thereon with an IR light-sensitive layer which comprises an acetal polymer having a specific structure I (R1 = C1-12 alkyl; R2 = substituted Ph or substituted 1-naphthyl; and R3 = carboxyalkyl, ethynyl or substituted phenyl), a polymeric compound carrying, on the side chains, fluorinated aliphatic groups in which the fluorinated aliphatic groups are those derived from fluorinated aliphatic compds. prepared by the telomerization or oligomerization; and a light-heat conversion substance. The light-sensitive **lithog.** printing plate is excellent in the both printing durability and the developing latitude.

IT **100-83-4D**, 3-Hydroxybenzaldehyde, cyclic acetals with polyvinyl alc. **123-72-8D**, Butyl aldehyde, cyclic acetals

with polyvinyl alc. **9002-89-5D**, Mowiol 3-98, cyclic acetals with Bu aldehyde and hydroxybenzaldehyde
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



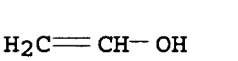
RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



RN 9002-89-5 HCAPLUS
CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O



IC ICM G03F007-00
INCL 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
ST IR sensitive **lithog** plate polyvinyl acetal fluoropolymer
IT **Lithographic** plates
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
IT Fluoropolymers, uses
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
IT Anhydrides
Polyvinyl acetals
(cyclic; IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
IT 65-85-0, Benzoic acid, uses 80-09-1, Bis(4-hydroxyphenyl) sulfone 85-42-7, Hexahydrophthalic anhydride 85-43-8, Tetrahydrophthalic anhydride 85-44-9, Phthalic anhydride 89-32-7, Pyromellitic anhydride 96-02-6, Chloromaleic anhydride 100-21-0, Terephthalic acid, uses **100-83-4D**, 3-Hydroxybenzaldehyde, cyclic acetals with polyvinyl alc. 108-30-5, Succinic anhydride, uses 108-31-6, Maleic anhydride, uses 117-08-8, Tetrachlorophthalic anhydride 123-08-0D, 4-Hydroxybenzaldehyde, cyclic acetals with polyvinyl alc. **123-72-8D**, Butyl aldehyde, cyclic acetals with polyvinyl alc. 624-67-9D, Propargyl aldehyde, cyclic acetals with polyvinyl alc. 708-06-5D, 2-Hydroxy-1-naphthaldehyde, cyclic

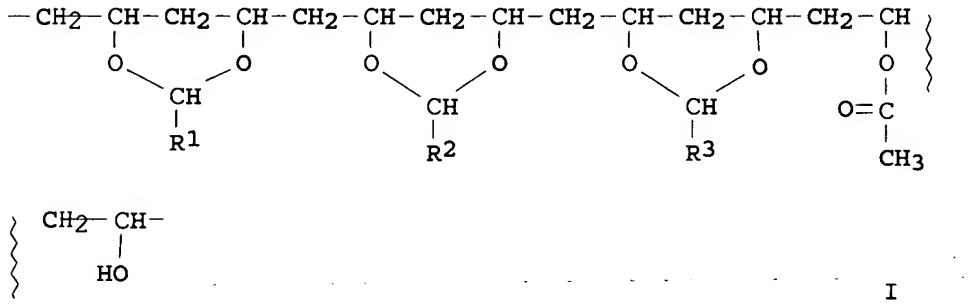
acetals with polyvinyl alc. 6766-44-5 **9002-89-5D**, Mowiol 3-98, cyclic acetals with Bu aldehyde and hydroxybenzaldehyde 36122-35-7, Phenylmaleic anhydride 117283-53-1 134127-48-3 644965-89-9, Megafac F 780F
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)

L62 ANSWER 4 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:1050638 HCAPLUS
DOCUMENT NUMBER: 143:356645
TITLE: Light-sensitive **lithographic** printing plate
INVENTOR(S): Nagashima, Akira
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: U.S. Pat. Appl. Publ., 14 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005214677	A1	20050929	US 2005-89480	20050325
JP 2005275229	A2	20051006	JP 2004-91360	20040326

PRIORITY APPLN. INFO.: JP 2004-91360 A 20040326

GI

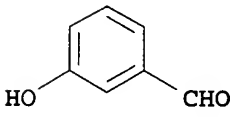


I

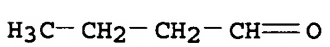
AB A light-sensitive **lithog.** printing plate comprising a hydrophilic substrate provided thereon with a layer sensitive to IR light rays comprising a polymer represented by the following general formula I (R1 = C1-12 alkyl; R2 = substituted Ph or naphthyl; R3 = carboxyalkyl, ethynyl or substituted phenyl); an organic acid and/or a cyclic acid anhydride; and a light-heat conversion substance. The light-sensitive **lithog.** printing plate is excellent in the both printing durability and the developing latitude.

IT **100-83-4D**, cyclic acetals with polyvinyl alc.
123-72-8D, Butanal, cyclic acetals with polyvinyl alc.
9002-89-5D, Mowiol 3-98, cyclic acetals with Bu aldehyde and hydroxybenzaldehyde
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)

RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



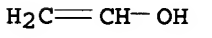
RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



RN 9002-89-5 HCAPLUS
CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O



IC ICM G03F007-00
INCL 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
ST IR sensitive **lithog** plate polyvinyl acetal
IT **Lithographic** plates
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
IT Anhydrides
Polyvinyl acetals
(cyclic; IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
IT 65-85-0, Benzoic acid, uses 80-09-1, Bis(4-hydroxyphenyl) sulfone 85-42-7, Hexahydrophthalic anhydride 85-43-8, Tetrahydrophthalic anhydride 85-44-9, Phthalic anhydride 89-32-7, Pyromellitic anhydride 96-02-6, Chloromaleic anhydride 100-02-7, p-Nitrophenol, uses 100-21-0, Terephthalic acid, uses **100-83-4D**, cyclic acetals with polyvinyl alc. 104-15-4, p-Toluenesulfonic acid, uses 108-30-5, Succinic anhydride, uses 108-31-6, Maleic anhydride, uses 117-08-8, Tetrachlorophthalic anhydride 123-08-0D, cyclic acetals with polyvinyl alc. **123-72-8D**, Butanal, cyclic acetals with polyvinyl alc. 124-04-9, Adipic acid, uses 624-67-9D, 2-Propynal, cyclic acetals with polyvinyl alc. 708-06-5D, 2-Hydroxy-1-naphthaldehyde, cyclic acetals with polyvinyl alc. 1571-33-1,

Phenylphosphonic acid 6766-44-5 **9002-89-5D**, Mowiol 3-98, cyclic acetals with Bu aldehyde and hydroxybenzaldehyde 36122-35-7, Phenylmaleic anhydride 117283-53-1 134127-48-3
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)

L62 ANSWER 5 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:16956 HCAPLUS
DOCUMENT NUMBER: 142:123213
TITLE: Development enhancement of **radiation**-sensitive elements
INVENTOR(S): Memetea, Livia T.; Jaramillo, Juana G.; Bradford, Nicholas; Goodin, Jonathan W.; Yang, Cheng; Levanon, Moshe
PATENT ASSIGNEE(S): Can.
SOURCE: U.S. Pat. Appl. Publ., 21 pp., Cont.-in-part of U.S. Ser. No. 647,910, abandoned.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 3
PATENT INFORMATION:

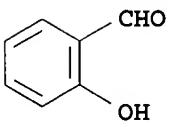
PATENT NO.	KIND	DATE	APPLICATION NO.		DATE
US 2005003296	A1	20050106	US 2004-800133		2004 0312
US 2004013965	A1	20040122	US 2003-388488		2003 0317
PRIORITY APPLN. INFO.:			US 2002-364078P	P	2002 0315
			US 2003-388488	A2	2003 0317
			US 2003-647910	B2	2003 0825

OTHER SOURCE(S): MARPAT 142:123213
AB A pos.-working **radiation**-sensitive composition for use with a **radiation** source comprises one or more polivinyl acetal polymers capable of being dissolved in an alkaline aqueous solution and a development-enhancing compound The sensitivity of a **radiation**-sensitive coating based on the composition of this invention is increased without compromising the handling characteristics. **Radiation**-sensitive elements based on the composition of the invention have good development latitude. A pos.-working **lithog.** printing precursor is based on the **radiation**-sensitive composition coated on a hydrophilic surface. The precursor is developable using an alkaline aqueous solution, and may be used with a **radiation** source in **lithog.** applications, such as conventional imaging systems, computer-to-plate systems or other direct imaging applications. The precursor is stable in its state before

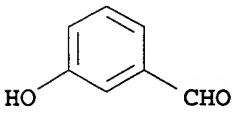
exposure and has an excellent handling property.

IT **90-02-8DP**, 2-Hydroxybenzaldehyde, reaction product with Ethenol homopolymer and butyraldehyde **100-83-4DP**, 3-Hydroxybenzaldehyde, reaction product with Ethenol homopolymer and butyraldehyde **123-72-8DP**, n-Butyraldehyde, reaction product with Ethenol homopolymer and Hydroxybenzaldehyde **9002-89-5DP**, Airvol 103, reaction product with hydroxybenzaldehyde and butyraldehyde
(development enhancement of **radiation**-sensitive elements containing)

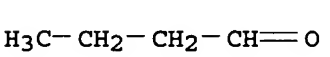
RN 90-02-8 HCAPLUS
CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



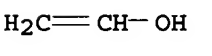
RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



RN 9002-89-5 HCAPLUS
CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O



IC ICM G03C001-76
INCL 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 38
ST development enhancement **radiation** sensitive element
IT **Lithography**
(development enhancement of **radiation**-sensitive elements containing)
IT **90-02-8DP**, 2-Hydroxybenzaldehyde, reaction product with Ethenol homopolymer and butyraldehyde **100-83-4DP**,

3-Hydroxybenzaldehyde, reaction product with Ethenol homopolymer and butyraldehyde **123-72-8DP**, n-Butyraldehyde, reaction product with Ethenol homopolymer and Hydroxybenzaldehyde **9002-89-5DP**, Airvol 103, reaction product with hydroxybenzaldehyde and butyraldehyde
(development enhancement of **radiation**-sensitive elements containing)

IT 50-84-0, 2,4-Dichlorobenzoic acid 62-23-7, 4-Nitrobenzoic acid 67-71-0, Dimethylsulfone 87-66-1, 1,2,3-Benzenetriol 89-84-9, 2',4'-Dihydroxyacetophenone 89-86-1, 2,4-Dihydroxybenzoic acid 90-15-3, 1-Naphthol 92-70-6 94-18-8, Benzyl-4-hydroxybenzoate 94-26-8, Butyl-4-hydroxybenzoate 95-14-7, 1H-Benzotriazole 97-29-0, 2,2',4,4'-Tetrahydroxydiphenyl sulfide 99-76-3, Methyl-4-hydroxybenzoate 108-46-3, Resorcinol, uses 118-55-8, Phenyl Salicylate 119-36-8, Methyl salicylate 121-79-9, Propyl gallate 121-92-6, 3-Nitrobenzoic acid 123-31-9, Hydroquinone, uses 131-56-6, 2,4-Dihydroxybenzophenone 136-36-7, Resorcinol monobenzoate 136-77-6, 4-Hexylresorcinol 552-16-9, 2-Nitrobenzoic acid 610-30-0, 2,4-Dinitrobenzoic acid 645-09-0, 3-Nitrobenzamide 1143-72-2, 2,3,4-Trihydroxybenzophenone 1948-33-0, tert-Butyl-hydroquinone 2150-47-2, 2,4-Dihydroxybenzoic acid methyl ester 2283-08-1, 2-Hydroxy-1-naphthoic acid 10288-28-5, 2-(Carbamoylazo)isobutyronitrile 18039-42-4, 5-Phenyl-1H-tetrazole 24207-41-8 62845-75-4
(development enhancement of **radiation**-sensitive elements containing)

L62 ANSWER 6 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:254170 HCAPLUS
DOCUMENT NUMBER: 138:262701
TITLE: Positive acting photoresist composition and imageable element
INVENTOR(S): Levanon, Moshe; Lurie, Emmanuel; Malikov, Sergei; Naigertsik, Oleg; Postel, Larisa
PATENT ASSIGNEE(S): Creo Il. Ltd., Israel
SOURCE: U.S., 15 pp., Cont.-in-part of U.S. 6,255,033.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6541181	B1	20030401	US 2000-625582	2000 0726
US 6255033	B1	20010703	US 1999-365279	1999 0730
ES 2218190	T3	20041116	ES 2000-949860	2000 0728
TW 573208	B	20040121	TW 2000-89126927	2000 1215

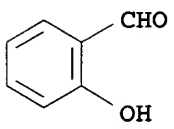
PRIORITY APPLN. INFO.: US 1999-365279 A2 1999

		0730
US 2000-625582	A	2000 0726
WO 2000-IB1147	A	2000 0728
IL 2000-140299	A	2000 1214
IN 2000-KO680	A	2000 1214

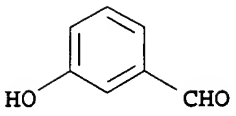
AB A pos. acting photoresist composition that can be heat-sensitive is presented, either coated on a **lithog.** base, or on a printing circuit board base, and comprises a water soluble heat-sensitive resin, a novel adhesion promoter and a **radiation** absorbing agent-a dye or a pigment. An excellent film forming polymer that comprises acetal units directly pendant from the polymer polyvinyl alc. backbone may be the only binder resin, when other resins being optional. The solubility of the coated material in the areas exposed to near -IR laser **radiation** in mild alkaline developers becomes considerably higher, allowing to obtain high resolved patterns of the etch-resistant material on printing circuit boards or **lithog.** printing plates. The composition can be applied on the substrate from a liquid of laminated as a dry film. Sensitizers may be added to render the composition sensitive to **radiation** in a non-thermal sense.

IT **90-02-8DP**, 2-Hydroxybenzaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde
100-83-4DP, 3-Hydroxybenzaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde
123-72-8DP, n-Butyraldehyde, cyclic acetals with poly(vinyl alc.) and react product with hydroxybenzaldehyde and/or glyoxylic acid and/or propargyl aldehyde and/or formylphenoxyacetic acid and/or isovaleraldehyde
(pos. acting photoresist composition and imageable element containing)

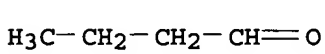
RN 90-02-8 HCAPLUS
CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



IC ICM G03C001-77
ICS G03C001-73; G03F007-039; G03F007-09
INCL 430275100; 430277100; 430278100; 430270100; 430905000; 430909000; 430944000; 430326000
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
IT **90-02-8DP**, 2-Hydroxybenzaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde **100-83-4DP**, 3-Hydroxybenzaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde 121-33-5DP, Vanillin, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde and hydroxybenzaldehyde 123-08-0DP, 4-Hydroxybenzaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde **123-72-8DP**, n-Butyraldehyde, cyclic acetals with poly(vinyl alc.) and react product with hydroxybenzaldehyde and/or glyoxylic acid and/or propargyl aldehyde and/or formylphenoxyacetic acid and/or isovaleraldehyde 298-12-4DP, Glyoxylic acid, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde and hydroxybenzaldehyde 590-86-3DP, Isovaleraldehyde, cyclic acetals with poly(vinyl alc.) and react product with formylphenoxyacetic acid and hydroxybenzaldehyde 624-67-9DP, Propargyl aldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde and hydroxybenzaldehyde 708-06-5DP, 2-Hydroxy-1-naphthaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde and hydroxybenzaldehyde 2973-77-5DP, 3,5-Dibromo-4-hydroxybenzaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde 22042-71-3DP, 4-Formylphenoxyacetic acid, cyclic acetals with poly(vinyl alc.) and react product with isovaleraldehyde and hydroxybenzaldehyde
(pos. acting photoresist composition and imageable element containing)
REFERENCE COUNT: 30 THERE ARE 30 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

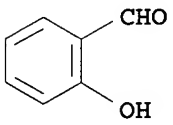
L62 ANSWER 7 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2001:493021 HCAPLUS
DOCUMENT NUMBER: 136:243278
TITLE: Field evaluation of non-pesticide chemicals as honey bee repellents
AUTHOR(S): Mayer, D. F.; Lunden, J. D.; Kovacs, G.; Miliczky, E. R.
CORPORATE SOURCE: Department of Entomology, Irrigated Agriculture Research & Extension Center,

Washington State University, Prosser, WA, 99350, USA
SOURCE: Colloques - Institut National de la Recherche Agronomique (2001), 98(Hazards of Pesticides to Bees), 159-168
CODEN: COLIEZ; ISSN: 0293-1915
PUBLISHER: Institut National de la Recherche Agronomique
DOCUMENT TYPE: Journal
LANGUAGE: English

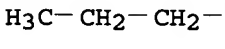
AB Bee poisoning from pesticides is a serious problem worldwide. Major concern exists for the safety of honey bees (Apis mellifera L.) as valuable pollinators of many horticultural crops. One way of reducing the pesticide hazard to bees is to apply a chemical repellent that will discourage bees from foraging on crops for an interval after a bee hazard pesticide has been applied. During 1990-1998, the authors conducted field tests on blooming apples (Malus domestica Borkh.), dandelions (Taraxacum officinale G. Weber, in Wiggers), buckwheat (officinale) and white Dutch clover (officinale) plants to evaluate their repellent effect to foraging honey bees. Evaluations were made by slowly walking through the plots and counting the number of honey bees (30 s/6.7 m/0.91 m swath) except for apples where they were counted by slowly moving around and counting the number of honey bees (30 s/1 tree) at 1 and 4 h. after application. The authors evaluated about 240 non-pesticide chems. Eleven chems. significantly reduced the number of honey bee foragers at 1 h. after application but not at 4 h. In some tests, but not all, 10 chems. significantly reduced the number of honey bee foragers at 1 h. after application but not at 4 h. One chemical significantly reduced the number of honey bee foragers at 1 h. and 4 h. after application. In some tests, but not all, 2 chems. significantly reduced the number of honey bee foragers at 4 h. after application but not at 1 h.

IT **90-02-8**, Salicylaldehyde, biological studies
123-72-8, Butyraldehyde
(field evaluation of non-pesticide chems. as honey bee repellents)

RN 90-02-8 HCAPLUS
CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



CC 5-4 (Agrochemical Bioregulators)
IT Apis mellifera
Artemisia
Cananga odorata
Cinnamomum zeylanicum
Eucalyptus **radiata**
Fagopyrum esculentum

Insect repellents
Lavandula
Malus pumila
Mentha piperita
Molasses
Ocimum basilicum
Origanum vulgare
Piper nigrum
Rosmarinus officinalis
Sorghum bicolor
Taraxacum officinale
Thymus (plant)
Trifolium
(field evaluation of non-pesticide chems. as honey bee repellents)

IT 54-12-6, Tryptophan 56-54-2, Quinidine 57-10-3, Palmitic acid, biological studies 57-11-4, Stearic acid, biological studies 60-24-2, 2-Mercaptoethanol 60-35-5, Acetamide, biological studies 64-10-8, Phenylurea 64-19-7, Acetic acid, biological studies 65-30-5 66-25-1, Hexanal 67-63-0, Isopropanol, biological studies 67-66-3, Chloroform, biological studies 67-68-5, Dimethyl sulfoxide, biological studies 71-23-8, Propanol, biological studies 71-36-3, 1-Butanol, biological studies 75-15-0, Carbon disulfide, biological studies 75-50-3, Trimethylamine, biological studies 75-65-0, 2-Methyl-2-propanol, biological studies 76-22-2, Camphor 78-70-6, Linalool 78-93-3, 2-Butanone, biological studies 79-16-3, N-Methylacetamide 79-31-2, Isobutyric acid 79-77-6, β-Ionone 80-59-1, Tiglic acid 83-34-1, Skatole 84-66-2, Diethylphthalate 87-44-5 89-83-8, Thymol **90-02-8**, Salicylaldehyde, biological studies 93-58-3, Methyl benzoate 94-96-2 95-48-7, o-Cresol, biological studies 97-53-0, Eugenol 99-03-6, 3'-Aminoacetophenone 99-76-3, p-Hydroxybenzoic acid methyl ester 100-41-4, Ethyl benzene, biological studies 100-52-7, Benzaldehyde, biological studies 101-31-5, l-Hyoscyamine 103-83-3, Dimethylbenzylamine 104-75-6, 2-Ethylhexylamine 106-35-4, 3-Heptanone 106-44-5, p-Cresol, biological studies 106-65-0, Succinic acid dimethyl ester 106-68-3, 3-Octanone 107-06-2, 1,2-Dichloroethane, biological studies 107-87-9, 2-Pentanone 108-05-4, Vinyl acetate, biological studies 108-31-6, Maleic anhydride, biological studies 108-95-2, Phenol, biological studies 110-12-3, 5-Methyl-2-hexanone 110-13-4, 2,5-Hexanedione 110-43-0, 2-Heptanone 110-54-3, n-Hexane, biological studies 110-93-0, 6-Methyl-5-hepten-2-one 111-13-7, 2-Octanone 111-27-3, 1-Hexanol, biological studies 111-84-2, n-Nonane 111-87-5, 1-Octanol, biological studies 112-14-1, Octylacetate 112-17-4, n-Decylacetate 112-37-8, Undecanoic acid 112-39-0, Palmitic acid methyl ester 112-44-7, Undecanal 119-61-9, Benzophenone, biological studies 120-72-9, Indole, biological studies 122-79-2, Phenyl acetate 123-11-5, p-Anisaldehyde, biological studies 123-19-3, 4-Heptanone **123-72-8**, Butyraldehyde 123-92-2, Isoamyl acetate 124-07-2, Caprylic acid, biological studies 125-12-2, Isobornyl acetate 133-06-2, Captan 135-19-3, β-Naphthol, biological studies 136-45-8, MGK repellent 326 138-86-3, Limonene 140-11-4, Benzyl acetate 142-62-1, n-Caproic acid, biological studies 142-82-5, n-Heptane, biological studies 147-85-3, L-Proline, biological studies 147-93-3, o-Mercaptobenzoic acid 328-50-7, α-Ketoglutaric acid 331-39-5, Caffeic acid 334-48-5,

Capric acid 458-37-7, Curcumin 470-82-6, Cineole 471-34-1, Calcium carbonate, biological studies 488-10-8, Jasmone 490-79-9, 2,5-Dihydroxybenzoic acid 499-75-2, Carvacrol 502-49-8, Cyclooctanone 506-12-7, Heptadecanoic acid 507-70-0, Borneol 540-84-1, 2,2,4-Trimethylpentane 544-63-8, Tetradecanoic acid, biological studies 546-49-6, Artemisia ketone 551-93-9, 2'-Aminoacetophenone 614-18-6, Ethyl nicotinate 624-92-0, Methyldisulfide 629-19-6, n-Propyl disulfide 638-53-9, Tridecanoic acid 705-86-2, δ-Decalactone 941-98-0, 1'-Acetonaphthone 1330-43-4, Sodium tetraborate 1337-83-3, Aldenal C 11 1596-84-5, Succinic acid 2,2-dimethylhydrazide 2016-57-1, Decylamine 2039-88-5, 2-Bromostyrene 2186-92-7, Anisaldehyde dimethylacetal 2315-68-6, n-Propyl benzoate 3391-86-4, 1-Octen-3-ol 3796-70-1, Geranylacetone 4602-84-0, Farnesol 7620-46-4, 9-Isothiocyanato acridine 7664-38-2, Phosphoric acid, biological studies 7704-34-9, Microthiol, biological studies 9004-99-3 12240-15-2, Prussian Blue 14371-10-9, trans-Cinnamaldehyde 20244-19-3 23422-53-9, Carzol 92SP 24804-31-7, Calcium oxalate hydrate 25414-22-6, 2-Methoxyfuran 27941-88-4, Amino acetophenone 36653-82-4, 1-Hexadecanol 41446-60-0, cis-7-Tetradecene 62242-52-8, Hexadecanone 70802-40-3 74214-63-4, β-Carboline-3-carboxylic acid 90823-38-4, Ro-Pel 116580-64-4, Margosan O 138261-41-3, NTN 33893-240FS 143350-75-8, Kinetic 404578-56-9, Algafer LPF 404580-56-9, Baitmate 404580-58-1, Can 17 404580-65-0, Compensol 404580-79-6, N-O-Dor II 404581-66-4, AeroSpray 404582-04-3, Epoleon N 100 404582-84-9, Scent-A-Way 404582-85-0, Sun Shield 404582-89-4, Terramark SPI 404582-90-7, Super Pepper Guard 404582-91-8, Free Shield 404582-94-1, Frost Shield 404583-18-2, Fruit Boost (insect attractant) 404583-20-6, Nutra-sol 404584-91-4, Get Off My Garden 404585-84-8, Uran 32 404586-91-0, X-O Deodorizer 404586-92-1, XP 201 404586-93-2, Y-Guard 404587-06-0, U-V-Killer
(field evaluation of non-pesticide chems. as honey bee repellents)

REFERENCE COUNT: 20 THERE ARE 20 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L62 ANSWER 8 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2001:101432 HCAPLUS
DOCUMENT NUMBER: 134:155248
TITLE: Positive acting photoresist composition and imaging element
INVENTOR(S): Levanon, Moshe; Lurie, Emmanuel; Malikov, Sergei; Postel, Larisa
PATENT ASSIGNEE(S): Creo, Ltd., Israel
SOURCE: PCT Int. Appl., 45 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2001009682	A2	20010208	WO 2000-IB1147	2000

				0728
WO 2001009682	A3	20010607		
W: AU, CA, JP, MX				
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
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				0730
CA 2380570	AA	20010208	CA 2000-2380570	
				2000
				0728
EP 1208014	A2	20020529	EP 2000-949860	
				2000
				0728
EP 1208014	B1	20040414		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI, CY				
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ES 2218190	T3	20041116	ES 2000-949860	
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TW 573208	B	20040121	TW 2000-89126927	
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PRIORITY APPLN. INFO.:			US 1999-365279	A
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			IL 2000-140299	A
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			IN 2000-KO680	A
				2000
				1214

AB The invention relates to laser direct imaging. A pos. acting, composition that can be heat-sensitive is presented, either coated on a lithog. base, or on a printing circuit board base, and comprises a H2O soluble heat-sensitive resin, a novel adhesion promoter and a radiation absorbing agent - a dye or a pigment. An excellent film forming polymer that comprises acetal units directly pendant from the polymer polyvinyl alc. backbone may be the only binder resin, when other resins being optional. The solubility of the coated material in the areas exposed to near-IR laser radiation in mild alkaline developers becomes considerably higher, allowing to obtain high resolved patterns of the etch-resistant material on printing

circuit boards or lithog. printing plates. The composition can be applied on the substrate from a liquid of laminated as a dry film. Sensitizers may be added to render the composition sensitive to radiation in a nonthermal sense.

IT **322413-98-9**, Vinyl alcohol-3-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol copolymer **322414-00-6**, Vinyl alcohol-2-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-glyoxylic acid copolymer **322414-02-8**, Vinyl alcohol-3-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-butyraldehyde-propargylaldehyde copolymer **322414-04-0**, Vinyl alcohol-2-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-3-methoxy-4-hydroxybenzaldehyde-butyraldehyde copolymer **322414-05-1**, Vinyl alcohol-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-2-hydroxy-1-naphthaldehyde-butyraldehyde copolymer **322414-06-2** **322414-08-4**, Vinyl alcohol-3,5-dibromo-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-butyraldehyde copolymer
(photoresist composition comprising pos. acting thermal resist layer containing acetal polymer)

RN 322413-98-9 HCAPLUS

CN Benzaldehyde, 3-hydroxy-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol and ethenol (9CI) (CA INDEX NAME)

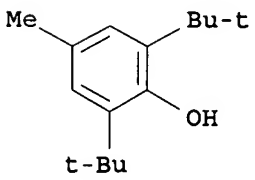
CM 1

CRN 557-75-5
CMF C2 H4 O

$H_2C{=}CH{-}OH$

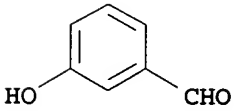
CM 2

CRN 128-37-0
CMF C15 H24 O



CM 3

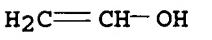
CRN 100-83-4
CMF C7 H6 O2



RN 322414-00-6 HCAPLUS
CN Acetic acid, oxo-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, ethenol and 2-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

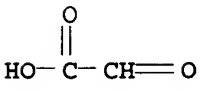
CM 1

CRN 557-75-5
CMF C2 H4 O



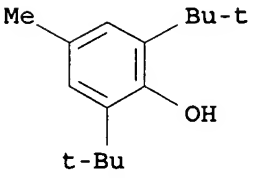
CM 2

CRN 298-12-4
CMF C2 H2 O3



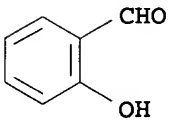
CM 3

CRN 128-37-0
CMF C15 H24 O



CM 4

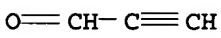
CRN 90-02-8
CMF C7 H6 O2



RN 322414-02-8 HCAPLUS
CN Benzaldehyde, 3-hydroxy-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, butanal, ethenol and 2-propynal (9CI) (CA INDEX NAME)

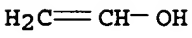
CM 1

CRN 624-67-9
CMF C3 H2 O



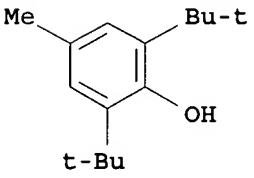
CM 2

CRN 557-75-5
CMF C2 H4 O



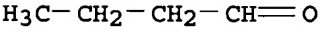
CM 3

CRN 128-37-0
CMF C15 H24 O



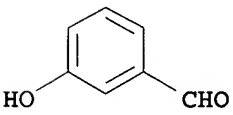
CM 4

CRN 123-72-8
CMF C4 H8 O



CM 5

CRN 100-83-4
CMF C7 H6 O2

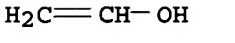


RN 322414-04-0 HCAPLUS
CN Benzaldehyde, 4-hydroxy-3-methoxy-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, butanal, ethenol and

2-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

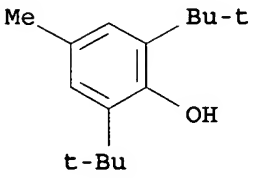
CM 1

CRN 557-75-5
CMF C2 H4 O



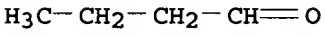
CM 2

CRN 128-37-0
CMF C15 H24 O



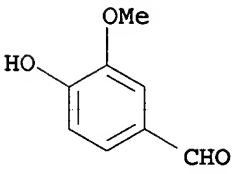
CM 3

CRN 123-72-8
CMF C4 H8 O



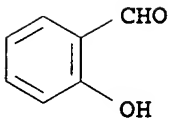
CM 4

CRN 121-33-5
CMF C8 H8 O3



CM 5

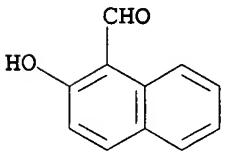
CRN 90-02-8
CMF C7 H6 O2



RN 322414-05-1 HCAPLUS
CN 1-Naphthalenecarboxaldehyde, 2-hydroxy-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, butanal, ethenol and 4-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

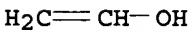
CM 1

CRN 708-06-5
CMF C11 H8 O2



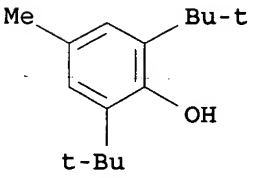
CM 2

CRN 557-75-5
CMF C2 H4 O



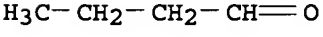
CM 3

CRN 128-37-0
CMF C15 H24 O



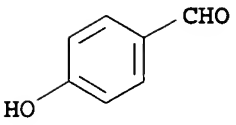
CM 4

CRN 123-72-8
CMF C4 H8 O



CM 5

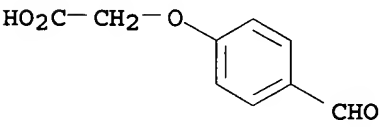
CRN 123-08-0
CMF C7 H6 O2



RN 322414-06-2 HCAPLUS
CN Acetic acid, (4-formylphenoxy)-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, ethenol, 2-hydroxybenzaldehyde and 3-methylbutanal (9CI) (CA INDEX NAME)

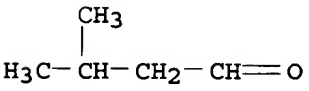
CM 1

CRN 22042-71-3
CMF C9 H8 O4



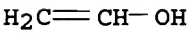
CM 2

CRN 590-86-3
CMF C5 H10 O



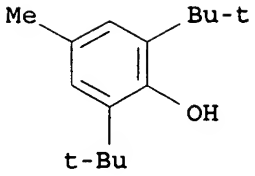
CM 3

CRN 557-75-5
CMF C2 H4 O



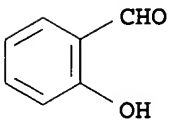
CM 4

CRN 128-37-0
CMF C15 H24 O



CM 5

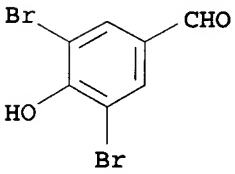
CRN 90-02-8
CMF C7 H6 O2



RN 322414-08-4 HCAPLUS
CN Benzaldehyde, 3,5-dibromo-4-hydroxy-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, butanal and ethenol (9CI) (CA INDEX NAME)

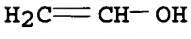
CM 1

CRN 2973-77-5
CMF C7 H4 Br2 O2



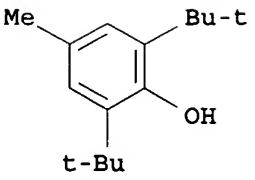
CM 2

CRN 557-75-5
CMF C2 H4 O



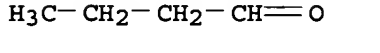
CM 3

CRN 128-37-0
CMF C15 H24 O



CM 4

CRN 123-72-8
CMF C4 H8 O



IC ICM G03F007-00
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 76
IT 322413-97-8, Vinyl alcohol-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol copolymer **322413-98-9**, Vinyl alcohol-3-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol copolymer **322414-00-6**, Vinyl alcohol-2-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-glyoxylic acid copolymer **322414-02-8**, Vinyl alcohol-3-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-butyraldehyde-propargylaldehyde copolymer **322414-04-0**, Vinyl alcohol-2-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-3-methoxy-4-hydroxybenzaldehyde-butyraldehyde copolymer **322414-05-1**, Vinyl alcohol-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-2-hydroxy-1-naphthaldehyde-butyraldehyde copolymer **322414-06-2 322414-08-4**, Vinyl alcohol-3,5-dibromo-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-butyraldehyde copolymer
(photoresist composition comprising pos. acting thermal resist layer containing acetal polymer)

L62 ANSWER 9 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:861214 HCAPLUS
DOCUMENT NUMBER: 134:49196
TITLE: Laser-sensitive composition for lithographic plate making
INVENTOR(S): Furukawa, Akira; Mitsui, Shinobu
PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000338669	A2	20001208	JP 1999-131080	1999

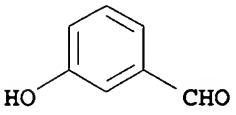
PRIORITY APPLN. INFO.: JP 1999-80653 A 0512 1999 0325

AB The title composition contains an azide and a polymer having oxazoline groups in the side chain. The composition provides a lithog. plate material of the high sensitivity and a lithog. plate of the high printability.

IT **100-83-4D**, 3-Hydroxybenzaldehyde, reaction product with polyvinyl alc.
(photoacid generator in laser-sensitive composition)

RN 100-83-4 HCAPLUS

CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



IT **9002-89-5DP**, PVA 105, reaction product with zinc acetate, o-hydroxybenzaldehyde, 4-cyanobenzaldehyde, or 2-aminoethanol
9002-89-5P, PVA 203
(polyvinyl alc. having oxazoline group)

RN 9002-89-5 HCAPLUS

CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O

$H_2C{=}CH{-}OH$

RN 9002-89-5 HCAPLUS

CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O

$H_2C{=}CH{-}OH$

IC ICM G03F007-038
ICS G03F007-00; G03F007-008

CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)

IT **100-83-4D**, 3-Hydroxybenzaldehyde, reaction product with polyvinyl alc. 42573-57-9 66003-76-7 69432-40-2
(photoacid generator in laser-sensitive composition)

IT 90-02-8DP, o-Hydroxybenzaldehyde, reaction product with modified poly(vinyl alc.) 105-07-7DP, 4-Cyanobenzaldehyde, reaction product with modified poly(vinyl alc.) 141-43-5P,

2-Aminoethanol, preparation 557-34-6DP, Zinc acetate, reaction product with modified poly(vinyl alc.) **9002-89-5DP**, PVA 105, reaction product with zinc acetate, o-hydroxybenzaldehyde, 4-cyanobenzaldehyde, or 2-aminoethanol **9002-89-5P**, PVA 203 30174-70-0P, Epocros WS 500 259144-30-4P, Epocros K 2010 (polyvinyl alc. having oxazoline group)

L62 ANSWER 10 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:705353 HCAPLUS
DOCUMENT NUMBER: 133:303569
TITLE: Light-sensitive composition for lithographic plate making
INVENTOR(S): Furukawa, Akira; Minato, Ken
PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000275823	A2	20001006	JP 1999-80652	1999 0325

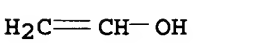
PRIORITY APPLN. INFO.: JP 1999-80652 1999 0325

AB The light-sensitive composition contains polyalkylene oxide, s-triazine substituted with a haloalkyl group or an oxadiazole, and an acid-sensitive crosslinking agent. The composition shows the excellent storage ability and provides a lithog. plate of the excellent printing characteristics.

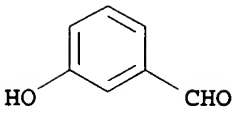
IT **9002-89-5P**, PVA 203
(polyalkylene oxide in light-sensitive material composition)
RN 9002-89-5 HCAPLUS
CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O



IT **100-83-4DP**, m-Hydroxybenzaldehyde, cyclic polyacetal with poly(vinyl alc.)
(polyalkylene oxide in light-sensitive material composition)
RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



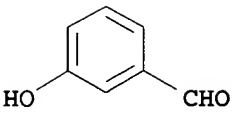
IC 'ICM G03F007-00
ICS G03F007-004; G03F007-038
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
IT **9002-89-5P**, PVA 203 127441-50-3DP, cyclic polyacetal with poly(vinyl alc.)
(polyalkylene oxide in light-sensitive material composition)
IT 57-55-6P, 1,2-Propanediol, preparation 64-19-7DP, Acetic acid, cyclic polyacetal with poly(vinyl alc.), preparation 90-02-8DP, o-Hydroxybenzaldehyde, polyvinyl acetal with poly(vinyl alc.) **100-83-4DP**, m-Hydroxybenzaldehyde, cyclic polyacetal with poly(vinyl alc.) 628-89-7DP, reaction products with poly(4-hydroxystyrene) 24979-70-2DP, reaction products with 2-(2-chloroethoxy)ethanol 312610-28-9DP, cyclic polyacetals with poly(vinyl alc.)
(polyalkylene oxide in light-sensitive material composition)

L62 ANSWER 11 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:705351 HCAPLUS
DOCUMENT NUMBER: 133:303567
TITLE: Light-sensitive **lithographic** plate material
INVENTOR(S): Furukawa, Akira
PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

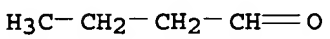
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000275821	A2	20001006	JP 1999-80650	1999 0325

PRIORITY APPLN. INFO.: JP 1999-80650 1999 0325

AB The light-sensitive **lithog.** plate material has a polyvinyl acetal, an azide, and a near-IR absorbing dye. The title material provides a **lithog.** plate of the high sensitivity and the excellent printing characteristics.
IT **100-83-4DP**, m-Hydroxybenzaldehyde, cyclic acetal with poly(vinyl alc.) **123-72-8DP**, Butyral, cyclic acetal with poly(vinyl alc.) **9002-89-5DP**, PVA 203, cyclic acetal with m-hydroxybenzaldehyde
(polyvinyl acetal in light-sensitive **lithog.** plate material)
RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



RN 9002-89-5 HCAPLUS
CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

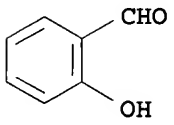
CM 1

CRN 557-75-5
CMF C2 H4 O

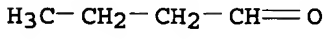
IC ICM G03F007-00
ICS G03F007-004; G03F007-008
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
ST light sensitive **lithog** plate vinyl benzal polymer
IT Polyvinyl acetals
(benzals; light-sensitive **lithog.** plate material)
IT Light-sensitive materials
Lithographic plates
(light-sensitive **lithog.** plate material)
IT Polyvinyl acetals
(polyvinyl acetal in light-sensitive **lithog.** plate material)
IT 5284-79-7 20237-98-3
(azide in light-sensitive **lithog.** plate material)
IT 55281-19-1 134127-48-3
(near-IR absorbing dye in light-sensitive **lithog.** plate material)
IT 64-19-7DP, Acetic acid, ester with vinyl alc., preparation **100-83-4DP**, m-Hydroxybenzaldehyde, cyclic acetal with poly(vinyl alc.) **123-72-8DP**, Butyral, cyclic acetal with poly(vinyl alc.) **9002-89-5DP**, PVA 203, cyclic acetal with m-hydroxybenzaldehyde
(polyvinyl acetal in light-sensitive **lithog.** plate material)

L62 ANSWER 12 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1999:219041 HCAPLUS
DOCUMENT NUMBER: 131:20159
TITLE: Chitosan staple fibers and their chemical modification with some aldehydes
AUTHOR(S): Hirano, Shigehiro; Nagamura, Kenji; Zhang, Min; Kim, Sun Ki; Chung, Byung Geul;

Yoshikawa, Masatoshi; Midorikawa, Takehiko
CORPORATE SOURCE: Chitin/Chitosan R and D, Tottori, 680, Japan
SOURCE: Carbohydrate Polymers (1999), 38(4), 293-298
CODEN: CAPOD8; ISSN: 0144-8617
PUBLISHER: Elsevier Science Ireland Ltd.
DOCUMENT TYPE: Journal
LANGUAGE: English
AB Nine wet-spinning conditions were examined for the preparation of chitosan staple fibers, and 5 novel N-alkylidene and N-arylidene-chitosan staple fibers were obtained by the post-treatment of the chitosan fibers with aldehydes including vanillin. The tenacity and elongation values of the chitosan filaments were almost unchanged by their post-treatment with aldehydes except that with formaldehyde and glyoxal. However, these values decreased significantly in the partially N-modified filaments which were obtained by the pretreatment with vanillin. The chitosan filaments (31-79 μm in diameter) had a scaly structure on the filament surface as examined by SEM observation.
IT **90-02-8DP**, 2-Hydroxybenzaldehyde, reaction products with chitosan **123-72-8DP**, n-Butyraldehyde, reaction products with chitosan
(chitosan staple fibers and their chemical modification with some aldehydes)
RN 90-02-8 HCAPLUS
CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



CC 40-3 (Textiles and Fibers)
IT 50-00-0DP, Formaldehyde, reaction products with chitosan, preparation **90-02-8DP**, 2-Hydroxybenzaldehyde, reaction products with chitosan 100-52-7DP, Benzaldehyde, reaction products with chitosan, preparation 107-22-2DP, Glyoxal, reaction products with chitosan 121-33-5DP, Vanillin, reaction products with chitosan 123-38-6DP, Propionaldehyde, reaction products with chitosan **123-72-8DP**, n-Butyraldehyde, reaction products with chitosan 9012-76-4DP, Chitosan, reaction products with aldehydes
(chitosan staple fibers and their chemical modification with some aldehydes)
REFERENCE COUNT: 21 THERE ARE 21 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L62 ANSWER 13 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1997:618277 HCAPLUS
DOCUMENT NUMBER: 127:301279
TITLE: A screen printing stencil

INVENTOR(S): Davidson, Robert Stephen; Palmer, Stuart John; Pratt, Julie E.; Wilson, Stephen Paul
PATENT ASSIGNEE(S): Sericol Ltd., UK; Davidson, Robert Stephen; Palmer, Stuart John; Pratt, Julie E.; Wilson, Stephen Paul
SOURCE: PCT Int. Appl., 40 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

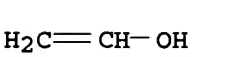
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9733202	A1	19970912	WO 1997-GB586	19970304
W: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, GH, HU, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, US, UZ, VN, YU, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
RW: GH, KE, LS, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG				
AU 9722247	A1	19970922	AU 1997-22247	19970304
EP 885408	A1	19981223	EP 1997-905323	19970304
EP 885408	B1	20011017		
R: CH, DE, ES, FR, GB, LI				
JP 2000506282	T2	20000523	JP 1997-531557	19970304
ES 2166063	T3	20020401	ES 1997-905323	19970304
US 5994033	A	19991130	US 1999-142021	19990602
PRIORITY APPLN. INFO.:			GB 1996-4578 A	19960304
			WO 1997-GB586 W	19970304

AB A screen printing stencil is made from a composition comprising polyhydroxy compds. having a plurality of 1,2- or 1,3-diol groups along a polymer backbone, the diol groups grafted thereto a compound of formula OHCA[X[(CH2)mO]nCOCR=CH2]p (A = an arylene or an alkylene group; X = O, S, a C-C bond, OCH2CO2, CO2, NR1; R = H or Me; R1 = C1-4 alkyl; m is an integer of from 1 to 8; n is an integer of from 1 to 3; and p is 1 or 2) or an acetal of the polyhydroxy compds. with ethylene glycol.

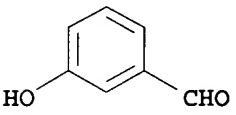
IT **9002-89-5DP**, Poly(vinyl alcohol), acetalized
(preparation and use in photosensitive compns. for manufacture of screen printing stencils)
RN 9002-89-5 HCAPLUS
CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O



IT **100-83-4P**, 3-Hydroxybenzaldehyde
(reaction in preparing photosensitive compns. for manufacture of screen printing stencils)
RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



IC ICM G03F007-12
ICS G03F007-038; G03F007-021
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
IT **9002-89-5DP**, Poly(vinyl alcohol), acetalized
(preparation and use in photosensitive compns. for manufacture of screen printing stencils)
IT **100-83-4P**, 3-Hydroxybenzaldehyde
(reaction in preparing photosensitive compns. for manufacture of screen printing stencils)

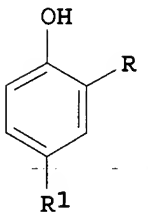
L62 ANSWER 14 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1996:738154 HCAPLUS
DOCUMENT NUMBER: 126:20139
TITLE: Sulfur dyes
INVENTOR(S): Cote, Philip N.; Domingo, Manuel Jose; Lan, Xiangfu; Shakhnovich, Alex I.
PATENT ASSIGNEE(S): Clariant Finance (Bvi) Limited, Virgin I. (Brit.)
SOURCE: Eur. Pat. Appl., 18 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 741168	A1	19961106	EP 1996-810271	1996 0429

EP 741168	B1	19990616		
R: BE, CH, DE, ES, FR, GB, IT, LI, PT				
ES 2135198	T3	19991016	ES 1996-810271	1996 0429
JP 08337733	A2	19961224	JP 1996-111743	1996 0502
CN 1143098	A	19970219	CN 1996-110039	1996 0502
BR 9602127	A	19980630	BR 1996-2127	1996 0502
US 5961670	A	19991005	US 1996-741484	1996 1030
HK 1012660	A1	20000505	HK 1998-113846	1998 1217
PRIORITY APPLN. INFO.:			US 1995-434422 A	1995 0503
			US 1996-598759 A	1996 0208
			TR 1996-348 A	1996 0426
			EP 1996-810271 A	1996 0429

OTHER SOURCE(S): MARPAT 126:20139

GI



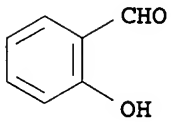
I

AB Sulfur dyes, with decreased tendering effect on fabrics, are manufactured by reaction of a S compound with phenols I (R, R1 = NO2, NO, or amino) and reaction of the product with ≥1 of an aldehyde, urea, a benzoquinone or a naphthoquinone, and monoethanolamine or by treating a sulfur dye already prepared from I with ≥1 of an aldehyde, benzoquinone or naphthoquinone, and monoethanolamine. A typical dye was manufactured heating 2,4-dinitrochlorobenzene 100.5, 50% NaOH 87, and water 400 g 1-1.5 h at 100°, slowly mixing the resulting dinitrophenolate

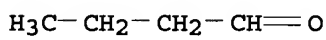
solution with a hot solution prepared from 45% aqueous NaSH.2H2O 89, S 72, and 50% NaOH 57.2 g at 90-100°, adding 50 g wash water from the phenolate reaction vessel, heating the reaction mixture 30 min at 104-106° while collecting 200 mL water, adding 700 g water, cooling to 35°, adding 28 g 40% glyoxal solution, heating the mixture 12 h at 122°, oxidizing the resulting solution 2 h at 65° by bubbling in O, adjusting the pH to 7.5, filtering, solubilizing the presscake (74 g) with 50% NaOH 30, 45% aqueous NaSH.2H2O 23.3, and water 89 g at 85°, and heating 2 h at 105°.

IT **90-02-8DP**, reaction products with desulfurized C.I. Sulfur Black 1 **123-72-8DP**, Butanal, reaction products with desulfurized C.I. Sulfur Black 1
(modified sulfur dyes for decreased tendering of fabrics)

RN 90-02-8 HCAPLUS
CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



IC ICM C09B049-00
CC 41-8 (Dyes, Organic Pigments, Fluorescent Brighteners, and Photographic Sensitizers)
Section cross-reference(s): 40

IT 50-00-0DP, Formaldehyde, reaction products with desulfurized C.I. Sulfur Black 1, preparation 57-13-6DP, Urea, reaction products with desulfurized C.I. Sulfur Black 1, preparation **90-02-8DP**, reaction products with desulfurized C.I. Sulfur Black 1 106-51-4DP, 2,5-Cyclohexadiene-1,4-dione, reaction products with desulfurized C.I. Sulfur Black 1, preparation 107-20-0DP, reaction products with desulfurized C.I. Sulfur Black 1 107-22-2DP, Glyoxal, reaction products with desulfurized C.I. Sulfur Black 1 111-30-8DP, Pentanedial, reaction products with desulfurized C.I. Sulfur Black 1 117-80-6DP, 2,3-Dichloro-1,4-naphthoquinone, reaction products with desulfurized C.I. Sulfur Black 1 118-75-2DP, 2,3,5,6-Tetrachloro-1,4-benzoquinone, reaction products with desulfurized C.I. Sulfur Black 1 **123-72-8DP**, Butanal, reaction products with desulfurized C.I. Sulfur Black 1 141-43-5DP, reaction products with C.I. Sulfur Black 1 298-12-4DP, reaction products with C.I. Sulfur Black 1 623-27-8DP, 1,4-Benzenedicarboxaldehyde, reaction products with desulfurized C.I. Sulfur Black 1 1326-82-5DP, C.I. Sulphur Black 1, desulfurized, derivs.
(modified sulfur dyes for decreased tendering of fabrics)

L62 ANSWER 15 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1991:515801 HCAPLUS
DOCUMENT NUMBER: 115:115801

TITLE: Epoxy resin compositions for sealing semiconductor devices
INVENTOR(S): Imura, Tetsuro; Ota, Masayuki; Fukuzawa, Takao
PATENT ASSIGNEE(S): Yuka Shell Epoxy K. K., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 03074426	A2	19910329	JP 1989-210106	1989 0816

PRIORITY APPLN. INFO.: JP 1989-210106 1989 0816

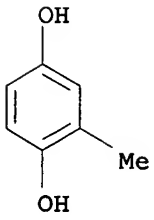
AB The title compns., giving cured products with good heat, moisture, and crack resistance, comprise epoxy resin hardeners, inorg. fillers, and epoxy resins with hydrolyzable halo content <1000 ppm, prepared from (2-methyl)epihalohydrin and novolak resins of reaction products of a (1 or 2 C1-9 alkyl or aryl-substituted) hydroquinone and an aldehyde or ketone selected from R1COR1, R2CO(CH2)mCOR2, R2CH:CHCOR2, R2COC6H3(OH)R3, and benzenedialdehyde [each R1 = H, C1-5 alkyl, (halo-substituted)Ph; each R2 = H, C1-5 alkyl, Ph; R3 = H, C1-5 alkyl, methoxy]. Thus, epichlorohydrin-treated formaldehyde-methylhydroquinone copolymer (I) 100.0, Epikote 5050 10.0, novolak phenol resin 79.8, RD-8 551.0, and additives 14 parts were blended, crushed, transfer molded, and cured 5 h at 170° to give samples having glass temperature 215°, crack resistance (cracked after 100 cycles of 5 min each at -50° and +200°) 0/20, and moisture resistance (50% failure in 120° vapor and 15 V bias voltage) 310 h, vs. 165, 5/20, and 210, resp., for samples containing Epikote 180S65 instead of I.

IT **135899-26-2D**, reaction products with epichlorohydrin
135942-51-7
(potting compns. containing, for semiconductors)

RN 135899-26-2 HCAPLUS
CN Benzaldehyde, 2-hydroxy-, polymer with 2-methyl-1,4-benzenediol (9CI) (CA INDEX NAME)

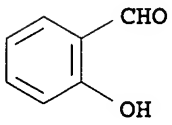
CM 1

CRN 95-71-6
CMF C7 H8 O2



CM 2

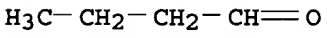
CRN 90-02-8
CMF C7 H6 O2



RN 135942-51-7 HCAPLUS
CN Butanal, polymer with formaldehyde and 1-(4-hydroxyphenyl)ethanone (9CI) (CA INDEX NAME)

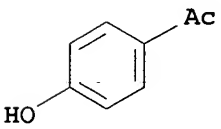
CM 1

CRN 123-72-8
CMF C4 H8 O



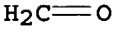
CM 2

CRN 99-93-4
CMF C8 H8 O2



CM 3

CRN 50-00-0
CMF C H2 O



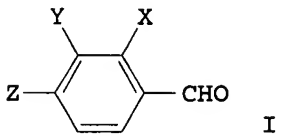
IC ICM C08G059-08
ICS C08G059-20; H01L023-29; H01L023-31
CC 37-6 (Plastics Manufacture and Processing)
Section cross-reference(s): 76
IT 106-89-8D, reaction products with novolak resins 117674-30-3D, reaction products with epichlorohydrin 135899-24-0D, reaction products with epichlorohydrin 135899-25-1D, reaction products with epichlorohydrin **135899-26-2D**, reaction products with epichlorohydrin 135899-27-3D, reaction products with epichlorohydrin **135942-51-7**
(potting compns. containing, for semiconductors)

L62 ANSWER 16 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1987:642675 HCAPLUS
DOCUMENT NUMBER: 107:242675
TITLE: Glutaraldehyde-aldehyde disinfecting and sterilizing compositions, particularly effective against tuberculosis bacteria
INVENTOR(S): Ascenzi, Joseph Michael; Gordon, Michael David; Bruckner, Norman Irving
PATENT ASSIGNEE(S): Surgikos, Inc., USA
SOURCE: Eur. Pat. Appl., 25 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 232996	A1	19870819	EP 1987-300538	19870122
EP 232996	B1	19900103		
R: AT, BE, CH, DE, ES, FR, GB, IT, LI, LU, NL, SE				
IN 164910	A	19890701	IN 1986-CA953	19861229
AU 8767878	A1	19870730	AU 1987-67878	19870121
AU 586064	B2	19890629		
CA 1314207	A1	19930309	CA 1987-527854	19870121
DK 8700363	A	19870724	DK 1987-363	19870122
JP 62201801	A2	19870905	JP 1987-11462	19870122
JP 07094361	B4	19951011		
BR 8700284	A	19871208	BR 1987-284	19870122
ZA 8700479	A	19880831	ZA 1987-479	19870122

AT 49101	E	19900115	AT 1987-300538	1987 0122
ES 2121730	T3	19981216	ES 1987-300538	1987 0122
PRIORITY APPLN. INFO.:			US 1986-821660	A 1986 0123
			EP 1987-300538	A 1987 0122

GI



I

AB Sterilizing and disinfecting solns., which are particularly effective against Mycobacterium tuberculosis and related species at 20°, contain 0.3-6 weight% glutaraldehyde and 0.01-0.6 weight% of a conjugated monoaldehyde selected from a) α,β-unsatd. C6-10 aldehydes R1CR2:CR3CHO (R1 = H, C1-3 hydrocarbyl, Ph; R2, R3 = H, Me), b) PhCHO, and c) substituted benzaldehydes I (X, Y = H, OH, halo; Z = H, OH, Me, OMe, halo, nitro; YZ = OCH2O; OH groups are not on adjacent C atoms). The addition of a number of α,β-unsatd. monoaldehydes to a 2% aqueous glutaraldehyde solution showed enhanced tuberculocidal activity. The glutaraldehyde solution alone showed 4.6 + 104 organisms (M. bovis BCG test organism)/4.40 + 105 initial organisms after 10 min and 2.4 + 103 after 30 min, at 20°. However, addition of 0.33 weight% 2-hexenal gave 0 organisms/4.5 + 105 initial organisms after 10 min., and 0.11 weight% PhCH:CMeCHO also gave 0/6.8 + 105 initial organisms after 10 min., at 20°.

IT **111645-71-7 111645-78-4 111645-79-5**
(disinfection and sterilization with, against tuberculosis bacteria)

RN 111645-71-7 HCAPLUS

CN Pentanedial, mixt. with butanal (9CI) (CA INDEX NAME)

CM 1

CRN 123-72-8
CMF C4 H8 O

CM 2

CRN 111-30-8

CMF C5 H8 O2

OHC— $(CH_2)_3$ — CHO

RN 111645-78-4 HCAPLUS
CN Pentanedial, mixt. with 2-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

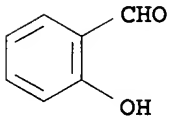
CM 1

CRN 111-30-8
CMF C5 H8 O2

OHC— $(CH_2)_3$ — CHO

CM 2

CRN 90-02-8
CMF C7 H6 O2



RN 111645-79-5 HCAPLUS
CN Pentanedial, mixt. with 3-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

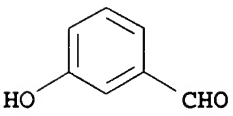
CM 1

CRN 111-30-8
CMF C5 H8 O2

OHC— $(CH_2)_3$ — CHO

CM 2

CRN 100-83-4
CMF C7 H6 O2



IC ICM A01N035-02
ICS A01N035-04

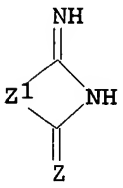
ICI A01N035-02; A01N035-04, A01N035-02
CC 63-8 (Pharmaceuticals)
IT 80411-13-8 111645-64-8 111645-65-9 111645-66-0 111645-67-1
111645-68-2 111645-69-3 111645-70-6 **111645-71-7**
111645-72-8 111645-73-9 111645-74-0 111645-75-1
111645-76-2 111645-77-3 **111645-78-4**
111645-79-5 111645-80-8 111645-81-9 111645-82-0
111645-83-1 111645-85-3, Glutaraldehyde-vanillin mixture
111645-86-4, Glutaraldehyde-isovanillin mixture 111645-87-5,
Glutaraldehyde-veratraldehyde mixture 111713-87-2
(disinfection and sterilization with, against tuberculosis bacteria)

L62 ANSWER 17 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1985:229534 HCAPLUS
DOCUMENT NUMBER: 102:229534
TITLE: Color imaging method and material
PATENT ASSIGNEE(S): Asahi Chemical Industry Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 59227485	A2	19841220	JP 1983-102830	19830610
JP 04016354	B4	19920323		

PRIORITY APPLN. INFO.: JP 1983-102830 19830610

GI



I

AB A color imaging method consists of contacting with heating, ≥1 compound selected from aromatic aldehydes and paraformaldehyde with ≥1 compound having the general formula I (Z = NH, (OR)2; R = lower alkyl; Z1 = aromatic or heterocyclic group that can form a conjugated system with C:NH group). The claim includes fixing procedure by which the imino group in I is inactivated and also the imaging material that contains ≥1 of the claimed 2 components in the receptor. The method and the material provide color images resistant to light and chems. Thus, 2 dispersions were prepared which resp. contained (A) 1,3-diimino-4,5,6,7-tetrachloroisoindoline 1, 5% aqueous poly(vinyl

alc.) 2, and H2O 2 parts, and added with 20% poly(vinyl alc.) 3 parts, and (B) 1,4-diformylbenzene 1, 5% poly(vinyl alc.) 2, and H2O 2 parts, and added with 20% poly(vinyl alc.) 3 parts. The 2 dispersions were mixed (1:1) and the mixture was coated on a plain paper sheet (3 g/m2). Application. of 140° heat with pressure produced blue-green coloration, which was unaffected by contact with dioctyl phthalate droplets for 1 wk. Exposure to sunlight for 15 days had no effect. Treating the colored material with a 10% solution of xylylene diisocyanate in PhMe fixed the image and reheating did not produce further coloration.

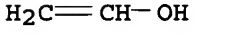
IT **9002-89-5**
(color-forming compns. containing aromatic aldehyde, imino compound and, for thermal recording materials)

RN 9002-89-5 HCAPLUS

CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

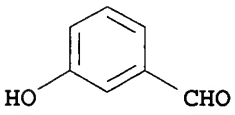
CRN 557-75-5
CMF C2 H4 O



IT **100-83-4**
(color-forming compns. containing imino compound and, for thermal recording materials)

RN 100-83-4 HCAPLUS

CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



IC ICM B41M005-18
ICS D06P001-42

CC 74-12 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)

IT 557-05-1 **9002-89-5**
(color-forming compns. containing aromatic aldehyde, imino compound and, for thermal recording materials)

IT 97-51-8 99-61-6 **100-83-4** 104-88-1, uses and miscellaneous 123-08-0 623-27-8 874-42-0 1122-91-4 30525-89-4
(color-forming compns. containing imino compound and, for thermal recording materials)

L62 ANSWER 18 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1963:412976 HCAPLUS

DOCUMENT NUMBER: 59:12976

ORIGINAL REFERENCE NO.: 59:2303a-c

TITLE: Diffusion coefficients of carbonyls in Raman spectroscopy

AUTHOR(S): Michel, Gilbert

CORPORATE SOURCE: Inst. Chim. Anal., Liege, Belg.

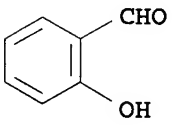
SOURCE: Bulletin des Societes Chimiques Belges (1963),

72, 125-48
CODEN: BSCBAG; ISSN: 0037-9646
DOCUMENT TYPE: Journal
LANGUAGE: Unavailable

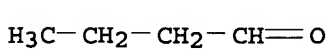
AB Correction terms are required to make intensity data taken on a variety of Raman spectrometers more directly comparable: exciting frequency and temperature, direction of exciting **radiation**, spectral response of detection system, n, and absorbance of diffusing medium. Tabulated data are expressed in terms of an internal standard (CCl4:459) by using Hg4358 at 23 ± 0.2° and a tube, diameter = 1 cm., length = 20 cm. of glass of n20D = 1.473. Diffusion coeffs. are based on the average of 3-8 results on each compound Expressing the results as a diffusion coefficient, the numerical values are given as the mean of a number of examples of each class, when the spread among members of the class is small: aliphatic esters, 0.077; aliphatic ketones, 0.091; alicyclic ketones 0.14. Thirteen tables give data on .apprx.130 compds. containing C:O and combinations of C:O and C:C, together with comparisons of other literature data when available. The data show the diffusion coefficient to be exalted in the sequence ester, ketone, aldehyde, and unsaturate. The coefficient for ketones runs from 0.082 in acetone to 3.1 in p-Me benzophenone; from 0.078 in EtOAc to 12.3 in cinnamaldehyde. 37 references.

IT **90-02-8**, Salicylaldehyde **123-72-8**, Butyraldehyde
(spectrum (Raman) of, line intensities of carbonyl group in, scattering coeffs. for)

RN 90-02-8 HCAPLUS
CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



CC 10 (Spectra and Some Other Optical Properties)

IT 60-01-5, Butyrin, tri- 62-23-7, Benzoic acid, p-nitro- 64-19-7, Acetic acid 70-11-1, Acetophenone, 2-bromo- 75-07-0, Acetaldehyde 76-49-3, Borneol, acetate 78-59-1, 2-Cyclohexen-1-one, 3,5,5-trimethyl- 78-94-4, 3-Buten-2-one 78-95-5, 2-Propanone, chloro- 79-20-9, Acetic acid, methyl ester 80-62-6, Methyl methacrylate 89-71-4, o-Toluic acid, methyl ester 89-98-5, Benzaldehyde, o-chloro- **90-02-8**, Salicylaldehyde 92-91-1, Acetophenone, 4'-phenyl- 94-30-4, p-Anisic acid, ethyl ester 96-22-0, 3-Pentanone 98-86-2, Acetophenone 98-88-4, Benzoyl chloride 99-36-5, m-Toluic acid, methyl ester 99-75-2, p-Toluic acid, methyl ester 99-90-1, Acetophenone, 4'-bromo- 99-91-2, Acetophenone, 4'-chloro- 99-92-3, Acetophenone, 4'-amino- 99-93-4, Acetophenone, 4'-hydroxy- 100-06-1, Acetophenone, 4'-methoxy- 100-19-6, Acetophenone, 4'-nitro- 100-47-0, Benzonitrile 100-52-7, Benzaldehyde 101-97-3, Acetic acid, phenyl-, ethyl ester

103-36-6, Cinnamic acid, ethyl ester 103-79-7, 2-Propanone, phenyl- 104-88-1, Benzaldehyde, p-chloro- 105-37-3, Propionic acid, ethyl ester 105-39-5, Acetic acid, chloro-, ethyl ester 105-53-3, Malonic acid, diethyl ester 105-54-4, Butyric acid, ethyl ester 107-87-9, 2-Pentanone 108-05-4, Vinyl acetate 108-10-1, 2-Pentanone, 4-methyl- 108-83-8, 4-Heptanone, 2,6-dimethyl- 109-49-9, 5-Hexen-2-one 110-13-4, 2,5-Hexanedione 118-61-6, Salicylic acid, ethyl ester 119-61-9, Benzophenone 120-47-8, Benzoic acid, p-hydroxy-, ethyl ester 120-92-3, Cyclopentanone 122-00-9, Acetophenone, 4'-methyl- 122-57-6, 3-Buten-2-one, 4-phenyl- 122-79-2, Acetic acid, phenyl ester 123-08-0, Benzaldehyde, p-hydroxy- 123-11-5, p-Anisaldehyde 123-19-3, 4-Heptanone 123-42-2, 2-Pentanone, 4-hydroxy-4-methyl- **123-72-8**, Butyraldehyde 123-86-4, Acetic acid, butyl ester 134-84-9, Benzophenone, 4-methyl- 135-02-4, o-Anisaldehyde 140-88-5, Acrylic acid, ethyl ester 462-18-0, 7-Tridecanone 504-20-1, 2,5-Heptadien-4-one, 2,6-dimethyl- 515-84-4, Acetic acid, trichloro-, ethyl ester 532-27-4, Acetophenone, 2-chloro- 563-80-4, 2-Butanone, 3-methyl- 565-80-0, 3-Pentanone, 2,4-dimethyl- 577-59-3, Acetophenone, 2'-nitro- 579-74-8, Acetophenone, 2'-methoxy- 587-04-2, Benzaldehyde, m-chloro- 591-31-1, m-Anisaldehyde 606-27-9, Benzoic acid, o-nitro-, methyl ester 606-45-1, o-Anisic acid, methyl ester 610-94-6, Benzoic acid, o-bromo-, methyl ester 610-96-8, Benzoic acid, o-chloro-, methyl ester 610-97-9, Benzoic acid, o-iodo-, methyl ester 611-97-2, Benzophenone, 4,4'-dimethyl- 618-32-6, Benzoyl bromide 618-91-7, Benzoic acid, m-iodo-, methyl ester 618-95-1, Benzoic acid, m-nitro-, methyl ester 619-42-1, Benzoic acid, p-bromo-, methyl ester 619-44-3, Benzoic acid, p-iodo-, methyl ester 623-50-7, Glycolic acid, ethyl ester 625-33-2, 3-Penten-2-one 638-10-8, Crotonic acid, 3-methyl-, ethyl ester 814-78-8, 3-Buten-2-one, 3-methyl- 1195-79-5, 2-Norbornanone, 1,3,3-trimethyl- 1754-55-8, Benzoic acid, 2,4,6-trimethyl-, ethyl ester 2142-73-6, Acetophenone, 2',5'-dimethyl- 2476-37-1, Acetophenone, 2',5'-dichloro- 2623-45-2, Acetophenone, 2-chloro-2',4'-dimethyl- 3637-01-2, Acetophenone, 3',4'-dimethyl- 4170-30-3, Crotonaldehyde 7335-27-5, Benzoic acid, p-chloro-, ethyl ester 10259-22-0, m-Anisic acid, ethyl ester 10544-63-5, Crotonic acid, ethyl ester 24398-88-7, Benzoic acid, m-bromo-, ethyl ester 89897-92-7, Crotonic acid, 3-methyl-, vinyl ester
(spectrum (Raman) of, line intensities of carbonyl group in, scattering coeffs. for)

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L3          376 SEA FILE=REGISTRY ABB=ON  PLU=ON  90-02-8/CRN
L4           25 SEA FILE=REGISTRY ABB=ON  PLU=ON  100-83-4/CRN
L5          214 SEA FILE=REGISTRY ABB=ON  PLU=ON  123-72-8/CRN
L6            1 SEA FILE=REGISTRY ABB=ON  PLU=ON  ETHANOL/CN
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L11           1 SEA FILE=REGISTRY ABB=ON  PLU=ON  123-72-8/RN
L15       56174 SEA FILE=REGISTRY ABB=ON  PLU=ON  46.248/RID
L16        1779 SEA FILE=REGISTRY ABB=ON  PLU=ON  L15 AND PMS/CI
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L25         552 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L3
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L27         426 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L5
L28           3 SEA FILE=HCAPLUS ABB=ON  PLU=ON  (L25 OR L26) AND L27
L29       11427 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L9
L30        2435 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L10
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L32         410 SEA FILE=HCAPLUS ABB=ON  PLU=ON  (L29 OR L30) AND L31
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L34           4 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L32 AND RADIAT?
L35           9 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L33 OR L34
L36      191327 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L6
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L42          14 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L24 OR L28 OR L33 OR
                L34 OR L35 OR L41
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L44         131 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L43(L)COMPOSITION?
L45           2 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L44 AND LITHOG?
L46          71 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L32 AND (L36 OR L37)
L47           0 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L46 AND PHOTOG?/SC,SX

L48           0 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L46 AND PHOTOG?
L50          20 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L44 AND PHOTOG?/SC
L51          14 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L42 OR L47 OR L48
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L53          20 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L52 NOT L51


=> d l53 1-20 ibib abs hitstr hitind

L53  ANSWER 1 OF 20  HCAPLUS  COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER:         2005:155470  HCAPLUS
DOCUMENT NUMBER:          142:249065
TITLE:                    Nanoparticle-filled stereolithographic resins
INVENTOR(S):              Steinmann, Bettina; Steinmann, Alfred
PATENT ASSIGNEE(S):       3D Systems, Inc., USA
SOURCE:                   Eur. Pat. Appl., 14 pp.
                          CODEN: EPXXDW
DOCUMENT TYPE:            Patent
LANGUAGE:                 English
FAMILY ACC. NUM. COUNT:   1
PATENT INFORMATION:

     PATENT NO.           KIND   DATE        APPLICATION NO.        DATE
     ---------------      ----   --------    --------------------
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     EP 1508834            A2    20050223    EP 2004-254005
                                                                   2004
                                                                   0702
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             MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ,
             EE, HU, PL, SK, HR
     US 2005040562         A1    20050224    US 2003-644299
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     JP 2005060673         A2    20050310    JP 2004-187526
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PRIORITY APPLN. INFO.: US 2003-644299 A 20030819

AB A liquid radiation-curable composition useful for the production of three dimensional articles by stereolithog. comprises: (a) at least one free-radical polymerizing organic substance; (b) at least one free-radical polymerization initiator; (d) at least one filler comprising silica-type nanoparticles suspended in the radiation-curable composition; (d) at least one cationically polymerizing organic substance; (e) at least one cationic polymerization initiator; (f) optionally, at least one hydroxyl-functional compound; and (g) optionally, at least one type of microparticle filler.

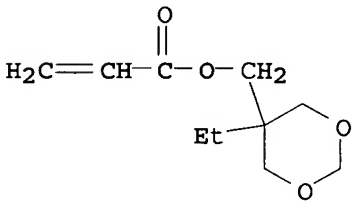
IT **189243-74-1**, Nanocryl XP 21/0765
(silica-filled; liquid radiation curable **composition** for nanoparticle-filled stereolithog. resins containing)

RN 189243-74-1 HCAPLUS

CN 2-Propenoic acid, (5-ethyl-1,3-dioxan-5-yl)methyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 66492-51-1
CMF C10 H16 O4



IC ICM G03F007-00
ICS G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)

IT 36446-02-3, Nanocryl XP 21/1045 57592-67-3, Nanocryl XP 21/0768
189243-74-1, Nanocryl XP 21/0765
(silica-filled; liquid radiation curable **composition** for nanoparticle-filled stereolithog. resins containing)

L53 ANSWER 2 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:695482 HCAPLUS
DOCUMENT NUMBER: 141:215780
TITLE: Transparent crosslinked resin composition containing glass filler
INVENTOR(S): Fukunishi, Masaaki; Shibahara, Sumio
PATENT ASSIGNEE(S): Sumitomo Bakelite Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

JP 2004238532	A2	20040826	JP 2003-29850	2003 0206

PRIORITY APPLN. INFO.: JP 2003-29850 2003 0206

AB The crosslinked composition contains a glass filler and a transparent resin comprising 1-99 weight% of a reactive monomer and/or oligomer and 1-99 weight% of an amorphous thermoplastic resin, which shows ≥80% transmission of light with wavelength 550 nm at 100-μm thickness. The composition is used as an optical sheet, a substrate for a display device, and an active matrix liquid crystal display device substrate, i.e., alternatives for glass substrates in optical devices.

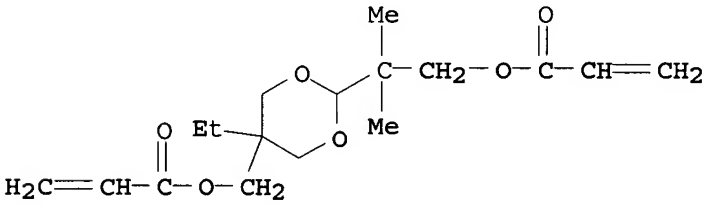
IT **573718-30-6P**
(transparent crosslinked resin **composition** containing glass filler as alternative for glass substrate in optical devices)

RN 573718-30-6 HCAPLUS

CN 2-Propenoic acid, bicyclo[2.2.1]heptane-2,3-diylbis(methylene) ester, polymer with [2-[1,1-dimethyl-2-[(1-oxo-2-propenyl)oxy]ethyl]-5-ethyl-1,3-dioxan-5-yl]methyl 2-propenoate (9CI) (CA INDEX NAME)

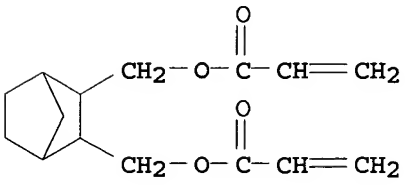
CM 1

CRN 87320-05-6
CMF C17 H26 O6



CM 2

CRN 79886-78-5
CMF C15 H20 O4



IC ICM C08L101-00
ICS C08K003-40; C08K005-101; G02F001-1333; H05B033-02; H05B033-14

CC 74-13 (Radiation Chemistry, Photochemistry, and

Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 57, 73

IT **573718-30-6P**
(transparent crosslinked resin **composition** containing glass filler as alternative for glass substrate in optical devices)

L53 ANSWER 3 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:695416 HCAPLUS
DOCUMENT NUMBER: 141:215718
TITLE: Coating composition containing photo-curable resin and thermal printing material
INVENTOR(S): Makabe, Yoshie; Kanda, Akira; Oya, Keiji
PATENT ASSIGNEE(S): Asahi Denka Kogyo K. K., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004237515	A2	20040826	JP 2003-27952	2003 0205

PRIORITY APPLN. INFO.: JP 2003-27952 2003 0205

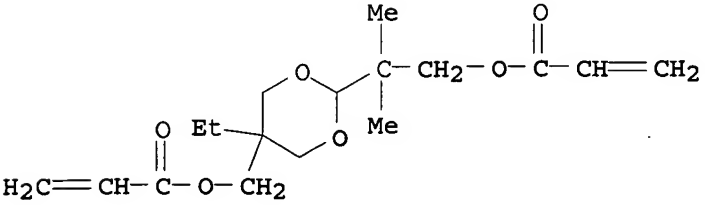
AB The composition contains (A) a color-former, (B) an organic color developer, (C) a photocurable resin composition, (D) a photo-curing agent, and (E) alicyclic amine and/or alicyclic amide compound bearing N in cyclic structure as a coloration preventing agent . Coated thermal printing material manufactured by coating and photo-curing the composition is also claimed. Coloration on photocuring is prevented, and the material gives clear color images.

IT **116321-27-8P**, Kayarad R 604 homopolymer
(coating **composition** containing photo-curable resin for thermal printing material)

RN 116321-27-8 HCAPLUS
CN 2-Propenoic acid, [2-[1,1-dimethyl-2-[(1-oxo-2-propenyl)oxy]ethyl]-5-ethyl-1,3-dioxan-5-yl]methyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 87320-05-6
CMF C17 H26 O6



IC ICM B41M005-30
ICS B41M005-26
CC 74-7 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 38
IT 28628-65-1P, Neopentyl glycol diacrylate homopolymer 57592-67-3P, 1,6-Hexanediol diacrylate homopolymer 88583-06-6P, Kayarad DPHA homopolymer **116321-27-8P**, Kayarad R 604 homopolymer 125086-52-4P 744222-17-1P
(coating **composition** containing photo-curable resin for thermal printing material)

L53 ANSWER 4 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:492523 HCAPLUS
DOCUMENT NUMBER: 139:60447
TITLE: Norbornene-based copolymer for photoresist, preparation method thereof, and photoresist composition comprising the same
INVENTOR(S): Han, Eun Sil; Moon, Bong Seok; Shin, Jung Han; Han, Ouck
PATENT ASSIGNEE(S): Samsung Electronics Co., Ltd., S. Korea
SOURCE: U.S. Pat. Appl. Publ., 13 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003118933	A1	20030626	US 2002-246474	2002 0919
US 6753127	B2	20040622		
KR 2003036948	A	20030512	KR 2001-67898	2001 1101
TW 593367	B	20040621	TW 2002-91104789	2002 0313
JP 2003183327	A2	20030703	JP 2002-307209	2002 1022

PRIORITY APPLN. INFO.: KR 2001-67898 A 2001 1101

AB Disclosed is an norbornene-based copolymer for photoresist, a preparation method thereof, and a photoresist composition comprising the same. The copolymer of the present invention exhibits high transparency to light of 193 nm wavelength and an excellent etching resistance, excellent resolution due to the remarkable difference between light-exposed part and light-unexposed part in the dissolving rate and excellent adhesion to the substrate due to very hydrophilic diketone group of its own. As a result, the copolymer of the present invention is very useful as ArF exposure photoresist material in the fabrication of semiconductor devices.
IT **547766-01-8 547766-03-0 547766-04-1**

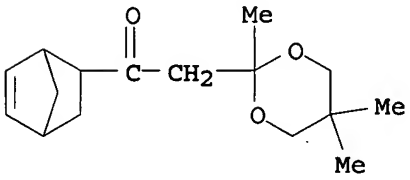
(copolymer in photoresist **composition**)

RN 547766-01-8 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, polymer with 1-bicyclo[2.2.1]hept-5-en-2-yl-1,3-butanedione, 1-bicyclo[2.2.1]hept-5-en-2-yl-2-(2,5,5-trimethyl-1,3-dioxan-2-yl)ethanone and 1,1-dimethylethyl bicyclo[2.2.1]hept-5-ene-2-carboxylate (9CI) (CA INDEX NAME)

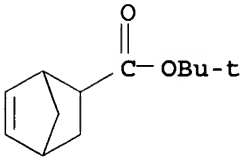
CM 1

CRN 547765-97-9
CMF C16 H24 O3



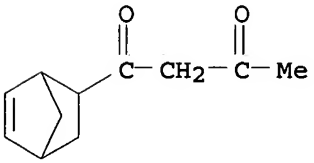
CM 2

CRN 154970-45-3
CMF C12 H18 O2



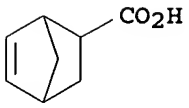
CM 3

CRN 52204-67-8
CMF C11 H14 O2



CM 4

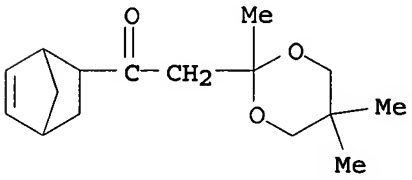
CRN 120-74-1
CMF C8 H10 O2



RN 547766-03-0 HCAPLUS
CN 1,3-Butanedione, 1-bicyclo[2.2.1]hept-5-en-2-yl-, polymer with bicyclo[2.2.1]hept-2-ene and 1-bicyclo[2.2.1]hept-5-en-2-yl-2-(2,5,5-trimethyl-1,3-dioxan-2-yl)ethanone (9CI) (CA INDEX NAME)

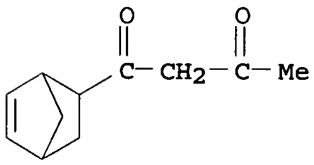
CM 1

CRN 547765-97-9
CMF C16 H24 O3



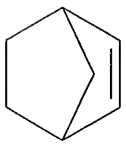
CM 2

CRN 52204-67-8
CMF C11 H14 O2



CM 3

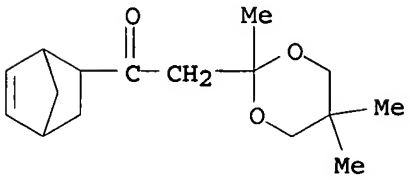
CRN 498-66-8
CMF C7 H10



RN 547766-04-1 HCAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with bicyclo[2.2.1]hept-2-ene, 1-bicyclo[2.2.1]hept-5-en-2-yl-1,3-butanedione and 1-bicyclo[2.2.1]hept-5-en-2-yl-2-(2,5,5-trimethyl-1,3-dioxan-2-yl)ethanone (9CI) (CA INDEX NAME)

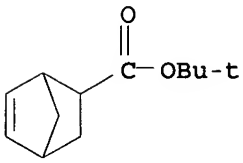
CM 1

CRN 547765-97-9
CMF C16 H24 O3



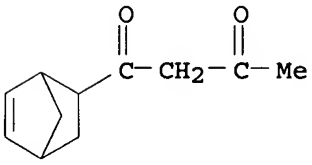
CM 2

CRN 154970-45-3
CMF C12 H18 O2



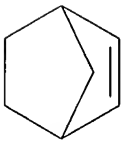
CM 3

CRN 52204-67-8
CMF C11 H14 O2



CM 4

CRN 498-66-8
CMF C7 H10



IC ICM G03F007-038

ICS G03F007-30; G03F007-38; C08F004-06; C08F004-40; C08F004-42; C08F010-00; C08F132-08; C08F136-00; C08F232-08; C07C049-105; C07C049-293; C07C049-297; C07C049-385; C07C049-403; C07D323-04; C07D319-12
INCL 430270100; 430326000; 430327000; 430330000; 430905000; 430914000; 526280000; 549367000; 549454000; 568374000
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
IT 107-21-1, Ethylene glycol, reactions 126-30-7, 2,2-Dimethyl-1,3-propane diol 141-78-6, Ethylacetate, reactions 504-63-2, 1,3-Propylenediol 2916-31-6, 2,2-Dimethyl-1,3-dioxolane 5063-03-6, 2-Acetyl-5-norbornene 195154-78-0 547765-96-8 547765-97-9 547765-98-0 547765-99-1 547766-00-7 **547766-01-8** 547766-02-9 **547766-03-0** **547766-04-1**
(copolymer in photoresist **composition**)
REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L53 ANSWER 5 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:222222 HCAPLUS
DOCUMENT NUMBER: 138:262687
TITLE: Chemically amplified negative photoresist, and photoresist composition
INVENTOR(S): Lee, Beom-Wook; Lim, Ik-Chul; Yoo, Seung-Joon
PATENT ASSIGNEE(S): Samsung SDI Co., Ltd., S. Korea
SOURCE: U.S. Pat. Appl. Publ., 14 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003054285	A1	20030320	US 2002-92846	20020307
US 6872502	B2	20050329		
KR 2002078485	A	20021019	KR 2001-17601	20010403
PRIORITY APPLN. INFO.:			KR 2001-17601 A	20010403

OTHER SOURCE(S): MARPAT 138:262687
GI

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

AB A polymer for a chemical amplified neg. photoresist and a photoresist composition are provided. A representative polymer of the invention is a compound of R1C(=CH2)R2R3 or R1C(+CH2)R4R5 (R1 = H, CH3; R2,4

=(R)α (CH2)β R', (R)α[(CH2)γ O]δ R';
R = CO, CO2, O, OCO, OCO2; R' = O, CO2, OCO2; α = 0, 1;
β = 0-5; γ = 1, 2; δ = 1-5; R3 = R6R7COR8OR9,
formula I, II, III (R6 which combines an acetal compound and a vinyl compound, is a C1-C5 saturated alkyl, C1-C5 ether, a C1-C5 carbonyl; R7-11 = H, C1-C5 saturated alkyls, C1-C5 ethers, C1-C5 carbonyl groups, C1-C5 alc. groups; m = 1-5); R5 is represented by formula IV (R12,13 = H or OH; * = the bonding site at which the R4 group is bonded)).

IT **502699-60-7P 502699-63-0P**
(preparation of polymer for chemical amplified neg. photoresist, and photoresist **composition**)

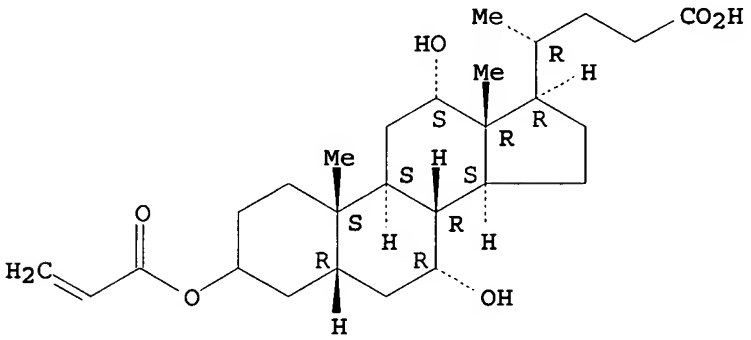
RN 502699-60-7 HCAPLUS

CN Cholan-24-oic acid, 7,12-dihydroxy-3-[(1-oxo-2-propenyl)oxy]-, (5β,7α,12α)-, polymer with 2-(1,3-dioxan-2-yl)ethyl 2-propenoate and 2-hydroxyethyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

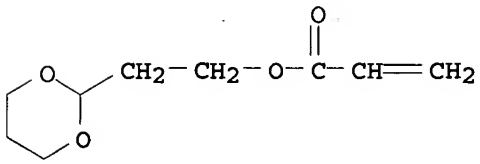
CRN 502699-57-2
CMF C27 H42 O6

Absolute stereochemistry.



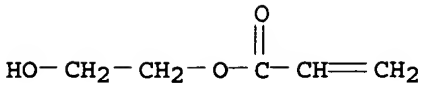
CM 2

CRN 14180-36-0
CMF C9 H14 O4



CM 3

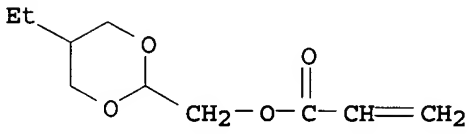
CRN 818-61-1
CMF C5 H8 O3



RN 502699-63-0 HCAPLUS
CN Cholan-24-oic acid, 7,12-dihydroxy-3-[(1-oxo-2-propenyl)oxy]-, (5α,7α,12α)-, polymer with (5-ethyl-1,3-dioxan-2-yl)methyl 2-propenoate, 2-hydroxyethyl 2-propenoate and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

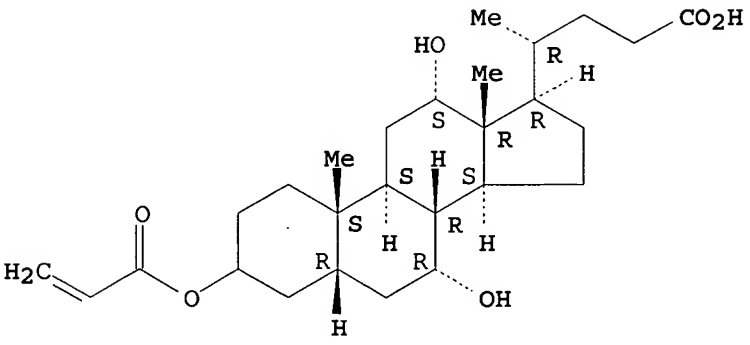
CRN 502699-62-9
CMF C10 H16 O4



CM 2

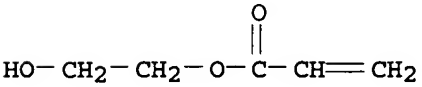
CRN 502699-57-2
CMF C27 H42 O6

Absolute stereochemistry.



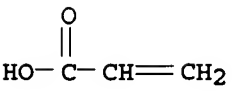
CM 3

CRN 818-61-1
CMF C5 H8 O3



CM 4

CRN 79-10-7
CMF C3 H4 O2



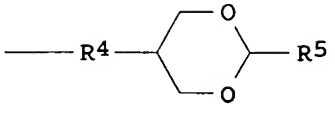
IC ICM G03F007-038
INCL 430270100; 526270000; 526266000; 526280000; 549369000; 549357000
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 35, 38
IT 502699-58-3P 502699-59-4P **502699-60-7P** 502699-61-8P **502699-63-0P** 502699-64-1P
(preparation of polymer for chemical amplified neg. photoresist, and photoresist **composition**)
REFERENCE COUNT: 21 THERE ARE 21 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L53 ANSWER 6 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2002:755238 HCAPLUS
DOCUMENT NUMBER: 137:286456
TITLE: Monomer and polymer for photoresist, photoresist composition, and phosphor layer composition for color cathode ray tube
INVENTOR(S): Lee, Beom-Wook; Lim, Ik-Chul; Yoo, Seung-Joon
PATENT ASSIGNEE(S): Samsung SDI Co., Ltd., S. Korea
SOURCE: U.S. Pat. Appl. Publ., 11 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002143130	A1	20021003	US 2002-76317	2002 0214
US 6699951	B2	20040302		
KR 2002077948	A	20021018	KR 2001-17600	2001 0403

PRIORITY APPLN. INFO.: KR 2001-17600 A 2001 0403

GI



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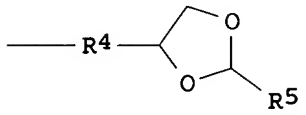


II

AB Disclosed are a monomer, a polymer for a photoresist, a photoresist composition and a phosphor layer for a cathode ray tube. The polymer has the formula: [(CH2-CR1R8-R9)a-(CH2-CR1R6-R7)b-(CH2-CR1R2-R3)c]n (R1 = H, CH3; R2 = (R)α (CH2)β R' or (R)β ((CH2)mO)γ R';R = CO, CO2, O, OCO, OC02; R' = O, CO2, OCO2; α = 0, 1; β = 0-5; m = 1, 2; γ = 1-5; R3 = I or II; R4, which combines an acetal compound and a vinyl compound, = C1-C5 alkyl, ether, carbonyl; R5 = C1-C5 alkyl, ether, carbonyl; R6,8 = single bond, (R)α (CH2)β R' or (R)β ((CH2)mO)γ R'; R7 = hydroxyl group; R9 = carboxyl group; a, b, and c each represent the mole ratio of its corresponding monomer, a and b = 0-0.99, and c = 0.01-0.3; and n = d.p. of each polymer and has a value of ≥ 2). The present invention relates to photoresist composition for a color cathode ray tube which causes no environmental pollution and has good storage stability and high sensitivity.

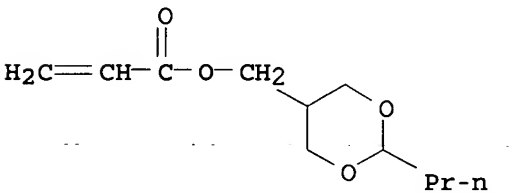
IT **464918-96-5P 464918-97-6P**
(monomer and polymer for photoresist **composition**, and phosphor layer **composition** for color cathode ray tube)

RN 464918-96-5 HCAPLUS

CN 2-Propenoic acid, 2-hydroxyethyl ester, polymer with (2-propyl-1,3-dioxan-5-yl)methyl 2-propenoate (9CI) (CA INDEX NAME)

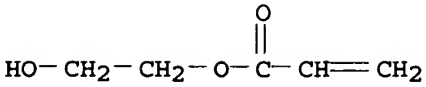
CM 1

CRN 464918-93-2
CMF C11 H18 O4



CM 2

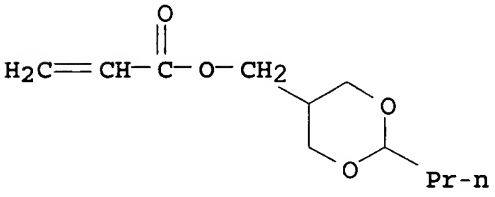
CRN 818-61-1
CMF C5 H8 O3



RN 464918-97-6 HCAPLUS
CN 2-Propenoic acid, polymer with 2-hydroxyethyl 2-propenoate and (2-propyl-1,3-dioxan-5-yl)methyl 2-propenoate (9CI) (CA INDEX NAME)

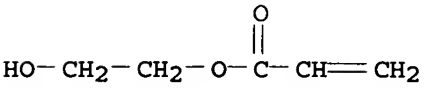
CM 1

CRN 464918-93-2
CMF C11 H18 O4



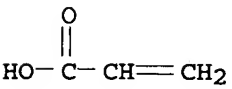
CM 2

CRN 818-61-1
CMF C5 H8 O3



CM 3

CRN 79-10-7
CMF C3 H4 O2



IC ICM C08F224-00
ICS C07D319-06; C07D317-44
INCL 526266000
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 35, 38
IT 464918-94-3P 464918-95-4P **464918-96-5P**
464918-97-6P
(monomer and polymer for photoresist **composition**, and phosphor layer **composition** for color cathode ray tube)

L53 ANSWER 7 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2001:524704 HCAPLUS
DOCUMENT NUMBER: 135:114408
TITLE: Photoelectrochemical cell comprising polymer electrolyte composition formed by polymerizing ionic liquid crystal monomer
INVENTOR(S): Ono, Michio
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 43 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1116769	A2	20010718	EP 2001-100999	2001 0117
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2001202995	A2	20010727	JP 2000-8054	2000 0117
US 2002034690	A1	20020321	US 2001-759363	2001 0116
US 6727023	B2	20040427		
PRIORITY APPLN. INFO.:			JP 2000-8054 A	2000 0117

OTHER SOURCE(S): MARPAT 135:114408
AB Disclosed is an electrolyte composition comprising a polymer compound formed by polymerizing an ionic liquid crystal monomer containing at least one polymerizable group. Also disclosed are an electrochem. cell, a nonaq. secondary cell and a photoelectrochem. cell, each comprising the electrolyte composition In accordance with the present invention, an electrolyte which does not substantially volatilize and exhibits excellent charge-transporting properties can be obtained, making it possible to obtain a photoelectrochem. cell having excellent photoelec. conversion properties and less deterioration of properties with time. Further, a lithium ion-conducting material having an extremely high ionic conductivity at low temps. can be obtained.
IT **350507-60-7P 350507-61-8P**
(electrolyte **composition** comprising polymer compound formed by polymerizing of ionic liquid crystal monomer for photoelectrochem. cell application)
RN 350507-60-7 HCAPLUS
CN Pyridinium, 4-(trans-5-decyl-1,3-dioxan-2-yl)-1-(19-oxo-3,6,9,12,15,18-hexaoxaheneicos-20-en-1-yl)-, iodide, homopolymer (9CI) (CA INDEX NAME)

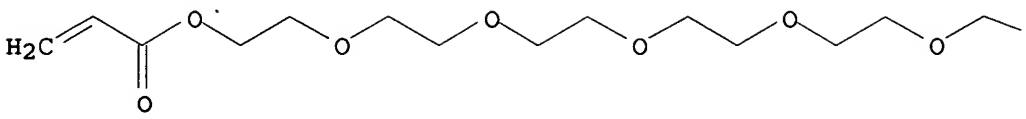
CM 1

CRN 350507-51-6

CMF C34 H58 N O9 . I

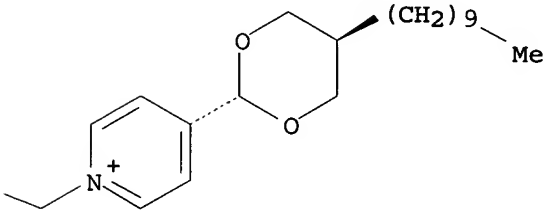
Relative stereochemistry.

PAGE 1-A



● I^-

PAGE 1-B



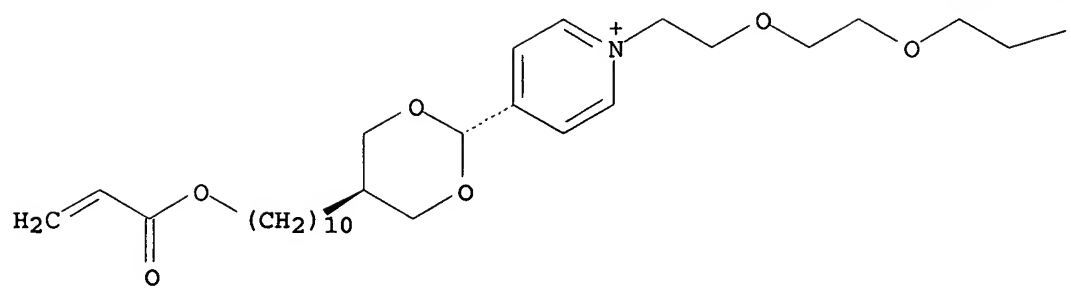
RN 350507-61-8 HCAPLUS
CN Pyridinium, 1,1'-(3,6,9,12,15-pentaoxaheptadecane-1,17-diyl)bis[4-[trans-5-[10-[(1-oxo-2-propenyl)oxy]decyl]-1,3-dioxan-2-yl]-, diiodide, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 350507-54-9
CMF C56 H90 N2 O13 . 2 I

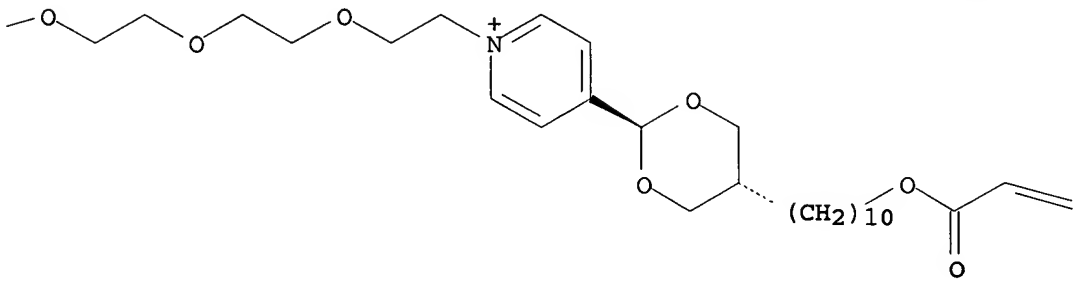
Relative stereochemistry.

PAGE 1-A



●2 I^-

PAGE 1-B



PAGE 1-C

$=CH_2$

IC ICM C09K019-00
ICS C09K019-38; H01G009-20
CC 74-1 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 72
IT **350507-60-7P 350507-61-8P** 350507-62-9P
350507-63-0P 350507-64-1P
(electrolyte **composition** comprising polymer compound formed by polymerizing of ionic liquid crystal monomer for photoelectrochem. cell application)

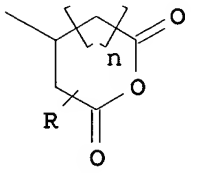
L53 ANSWER 8 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2001:62632 HCAPLUS
DOCUMENT NUMBER: 134:139210
TITLE: Resin for resists and chemical amplification resist composition
INVENTOR(S): Fujiwara, Tadayuki; Wakisaka, Yukiya; Toyama, Masayuki; Murata, Tadashi
PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

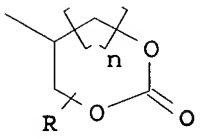
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001022073	A2	20010126	JP 1999-198161	19990712

PRIORITY APPLN. INFO.: JP 1999-198161 19990712

GI



I



II

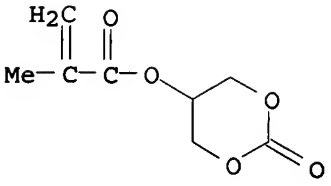
AB The title resin, which becomes soluble in aqueous alkali solns. by the action of acid, comprises a monomer unit having ≥1 structure selected from I and II (R = H or alkyl; n = 0-4) and the chemical amplification resist composition contains the resin and a photoacid generator. The resin and resist composition show high adhesion to substrates and photosensitivity and are especially useful in deep UV excimer laser and electron beam **lithog.**

IT **321660-48-4P 321660-50-8P**
(chemical amplification resist **composition** for **lithog**.)

RN 321660-48-4 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-oxo-1,3-dioxan-5-yl ester, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene and 4-ethenylphenol (9CI) (CA INDEX NAME)

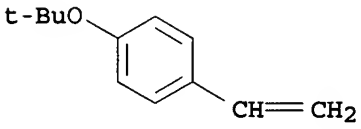
CM 1

CRN 321660-47-3
CMF C8 H10 O5



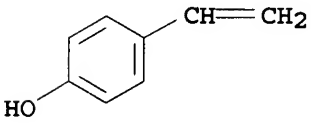
CM 2

CRN 95418-58-9
CMF C12 H16 O



CM 3

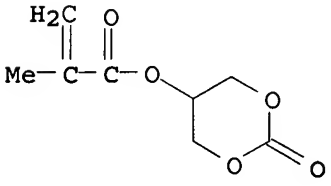
CRN 2628-17-3
CMF C8 H8 O



RN 321660-50-8 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2-oxo-1,3-dioxan-5-yl 2-methyl-2-propenoate and tetrahydro-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

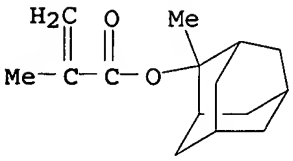
CM 1

CRN 321660-47-3
CMF C8 H10 O5



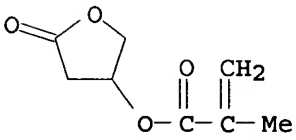
CM 2

CRN 177080-67-0
CMF C15 H22 O2



CM 3

CRN 130224-95-2
CMF C8 H10 O4



IC ICM G03F007-039
ICS C08F220-26; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 38
ST chem amplification resist **lithog**; acrylic polymer acid anhydride group resist; dioxanone group acrylic polymer resist
IT Electron beam **lithography**
Resists
(chemical amplification resist composition for **lithog.**)
IT 321660-46-2P **321660-48-4P** 321660-49-5P
321660-50-8P
(chemical amplification resist **composition** for **lithog**.)
IT 66003-78-9, Triphenylsulfonium triflate
(chemical amplification resist composition for **lithog.**)

L53 ANSWER 9 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:823000 HCAPLUS
DOCUMENT NUMBER: 133:367848
TITLE: Positive-working resist composition
INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiko; Aogo, Toshiaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 32 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 5
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

JP 2000321771	A2	20001124	JP 1999-127296	1999 0507
US 6596458	B1	20030722	US 2000-563436	2000 0503
TW 546548	B	20030811	TW 2000-89108532	2000 0504

PRIORITY APPLN. INFO.:

JP 1999-127296 A 1999 0507

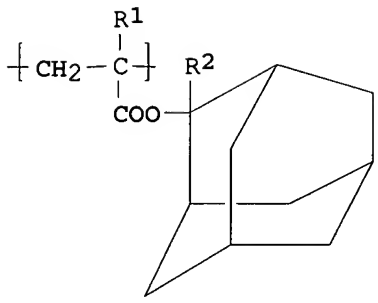
JP 1999-186607 A 1999 0630

JP 1999-193601 A 1999 0707

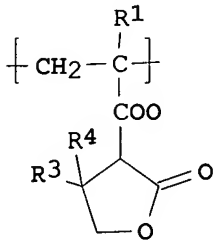
JP 1999-193602 A 1999 0707

JP 1999-193603 A 1999 0707

GI



I



II

AB The title resist composition contains (a) a resin which has repeating units I, II, and ≥1 selected from CH2CR1(CO2H),

CH2CR1[XOCR5R7CR6R8O(CR9R10CR11R12O)mR], CH2CR1(ZR13AR14), and CH2CR1(CO2R15SO2OR16) [R1 = H, Me; R2 = C1-4 alkyl; R3, R4 = H, C1-4 alkyl; R5-12 = H, (substituted) alkyl; R = H, (substituted) alkyl, (substituted) cycloalkyl, (substituted) aryl, (substituted) aralkyl; m = 1-10; X = single bond, (substituted) alkylene, (substituted) cycloalkylene, (substituted) arylene, divalent group which is composed of ≥1 group selected from ether, thioether, carbonyl, ester, amide, sulfonamide, urethane, and urea groups and is not decomposed by the action of acid; Z = single bond, ether, ester, amide, alkylene, divalent group composed of these groups; R13 = single bond, alkylene, arylene, divalent group composed of these groups; R14 = (substituted) alkyl, (substituted) cycloalkyl, (substituted) aryl, (substituted) aralkyl; R15 = alkylene, arylene, divalent group composed of these groups; R16 = H, (substituted) alkyl, (substituted) cycloalkyl, (substituted) alkenyl, (substituted) aryl, (substituted) aralkyl; A = CONHSO2, SO2NHCO, NHCONHSO2, SO2NHCONH, OCONHSO2, SO2NHCO2, SO2NHSO2] and of which the dissoln. rate to alkaline developing solns. is increased by the action of acid and (b) a compound that generates an acid by irradiation with actinic ray or radiation. The composition shows improved applicability to micro-photo-fabrication using far UV rays, especially ArF excimer laser beams and developability and provides resist patterns with good profile and high resolution contact holes.

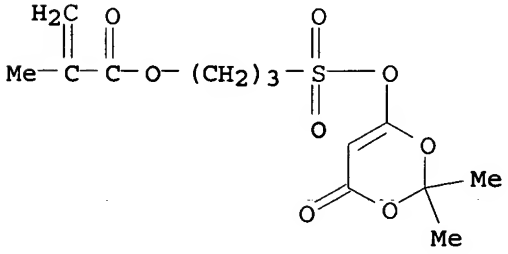
IT **307976-36-9P**
(pos. photoresist **composition** containing acrylic polymer and acid generator)

RN 307976-36-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[[(2,2-dimethyl-4-oxo-4H-1,3-dioxin-6-yl)oxy]sulfonyl]propyl ester, polymer with 2-ethyltricyclo[3.3.1.13,7]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

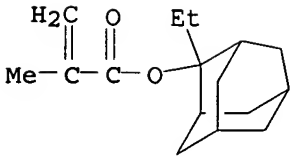
CM 1

CRN 307976-35-8
CMF C13 H18 O8 S



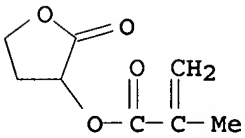
CM 2

CRN 209982-56-9
CMF C16 H24 O2



CM 3

CRN 195000-66-9
CMF C8 H10 O4



IC ICM G03F007-039
ICS C08F220-04; C08F220-18; C08F220-28; C08K005-00; C08L033-02; C08L033-04; G03F007-004; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 38
IT 288303-52-6P, Butyrolactone methacrylate-methacrylic acid-2-methyl-2-adamantyl methacrylate copolymer 307976-24-5P 307976-25-6P 307976-26-7P 307976-27-8P 307976-28-9P 307976-29-0P 307976-30-3P 307976-32-5P 307976-33-6P 307976-34-7P **307976-36-9P** 307976-37-0P 307976-39-2P
(pos. photoresist **composition** containing acrylic polymer and acid generator)

L53 ANSWER 10 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:619466 HCAPLUS
DOCUMENT NUMBER: 133:230376
TITLE: Monomer for crosslinking agent used in far UV-sensitive negative-working photoresist production, photoresist composition using same, and method for pattern formation for semiconductor device fabrication using same
INVENTOR(S): Kong, Geun Kyn; Chung, Jae Chang; Kim, Myung Soo; Kim, Hyung Ki; Kim, Hyung soo; Paek, Ki Ho
PATENT ASSIGNEE(S): Hyundai Electronics Industries Co., Ltd., S. Korea
SOURCE: Jpn. Kokai Tokkyo Koho, 19 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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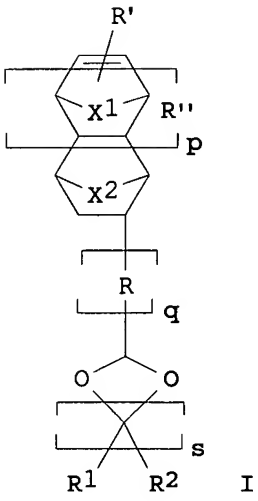
JP 2000239436	A2	20000905	JP 2000-43101	2000 0221
KR 2000056467	A	20000915	KR 1999-5807	1999 0222
TW 491875	B	20020621	TW 2000-89101780	2000 0202
US 6312868	B1	20011106	US 2000-501096	2000 0209
US 2002019560	A1	20020214	US 2001-954680	2001 0911
US 6399792	B2	20020604		

PRIORITY APPLN. INFO.:

KR 1999-5807	A	1999 0222
US 2000-501096	A3	2000 0209

GI



I

AB The invention relates to a crosslinking agent for photoresist composition, wherein the crosslinking agent has structure I (X1-2 = CH2, CH2CH2, O, S; p, s = 0-5 integer; q = 0,1; R', R'' = H, methyl; R = C1-10 alkyl, ether, ester, ketone, etc.; R1-2 = C1-10 alkyl, ester, ketone, etc.). The crosslinking agent provides a resist of the high sensitivity.

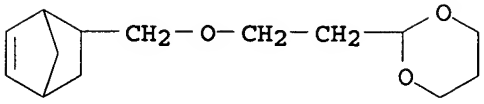
IT **291519-62-5P**
(crosslinking agent in photoresist **composition**)

RN 291519-62-5 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, polymer with 2-[2-(bicyclo[2.2.1]hept-5-en-2-ylmethoxy)ethyl]-1,3-dioxane and 2,5-furandione (9CI) (CA INDEX NAME)

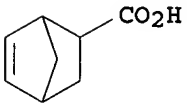
CM 1

CRN 291519-60-3
CMF C14 H22 O3



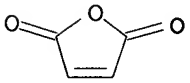
CM 2

CRN 120-74-1
CMF C8 H10 O2



CM 3

CRN 108-31-6
CMF C4 H2 O3



IC ICM C08K005-156
ICS C08F032-08; C08L101-00; G03F007-038; G03F007-30; G03F007-32
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 35, 76
IT 291519-61-4P **291519-62-5P**
(crosslinking agent in photoresist **composition**)

L53 ANSWER 11 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:274595 HCAPLUS
DOCUMENT NUMBER: 132:315851
TITLE: Photosensitive polymer compositions with high dry etching resistance and pattern formation using them
INVENTOR(S): Gokochi, Toru; Shinoda, Naomi; Asakawa, Koji; Okino, Takeshi
PATENT ASSIGNEE(S): Toshiba Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 28 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000122294	A2	20000428	JP 1999-70591	19990316
JP 3763693	B2	20060405		
JP 2001188351	A2	20010710	JP 2000-351365	19990316
US 2002098441	A1	20020725	US 2001-884977	20010621
US 6541597	B2	20030401		
US 2003149225	A1	20030807	US 2002-246619	20020919
US 6660450	B2	20031209		
US 2004043324	A1	20040304	US 2003-635571	20030807
US 6824957	B2	20041130		
JP 2004285077	A2	20041014	JP 2004-163529	20040601
JP 2004331981	A2	20041125	JP 2004-163504	20040601
US 2005031990	A1	20050210	US 2004-937577	20040910
US 2005031991	A1	20050210	US 2004-937853	20040910
US 2005037283	A1	20050217	US 2004-937313	20040910
US 2005037284	A1	20050217	US 2004-937357	20040910
US 7029823	B2	20060418		
US 2005048400	A1	20050303	US 2004-937832	20040910
PRIORITY APPLN. INFO.:			JP 1998-225747 A	19980810
			JP 1998-269320 A	19980924
			JP 1999-70591 A3	19990316
			JP 2000-351365 A3	1999

0316

US 1999-401181 A3
1999
0923

US 2001-884977 A3
2001
0621

US 2002-246619 A1
2002
0919

US 2003-635571 A1
2003
0807

AB The compns. contain (A) acid generators and (B) polymers containing ≥2 5-, 6-, or 7-membered-based bridged alicyclic structures having ≥1 C bonded to O via double bonds. Patterns are obtained by forming films of the compns., exposing with chemical radiation, heating, and developing with alkali aqueous solns. This method is useful for manufacture of semiconductor devices. The compns. show high transparency for short-wavelength light and give patterns with high resolution and good adhesion by alkali development.

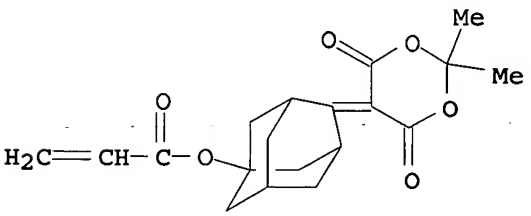
IT **265999-30-2P**
(dry etching-resistant photosensitive **compns.** containing bridged alicyclic polymers for pattern formation)

RN 265999-30-2 HCAPLUS

CN 2-Propenoic acid, 4-(2,2-dimethyl-4,6-dioxo-1,3-dioxan-5-ylidene)tricyclo[3.3.1.13,7]dec-1-yl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (1:1) (9CI) (CA INDEX NAME)

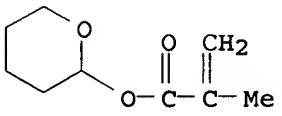
CM 1

CRN 265999-28-8
CMF C19 H22 O6



CM 2

CRN 52858-59-0
CMF C9 H14 O3



IC ICM G03F007-039
ICS G03F007-032; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 38, 76
IT 265999-29-9P **265999-30-2P** 265999-31-3P 265999-36-8P 265999-37-9P
(dry etching-resistant photosensitive **compns.** containing bridged alicyclic polymers for pattern formation)

L53 ANSWER 12 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1998:427845 HCAPLUS
DOCUMENT NUMBER: 129:154687
TITLE: Transparent resins, photosensitive compositions thereof, and pattern formation using the same, with excellent transparency to long-wavelength light, dry etching resistance, and high contrast and resolution
INVENTOR(S): Gokochi, Toru; Asakawa, Koji; Okino, Takeshi; Shinoda, Naomi; Nakase, Atsushi; Hayase, Rumiko; Kawamonzen, Yoshihiro
PATENT ASSIGNEE(S): Toshiba Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 33 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10171120	A2	19980626	JP 1997-272534	1997 1006
JP 3667956	B2	20050706		
US 6071670	A	20000606	US 1997-948425	1997 1010

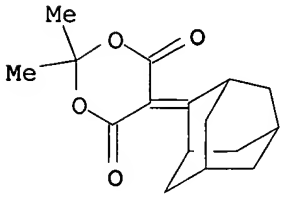
PRIORITY APPLN. INFO.: JP 1996-269758 A 1996 1011

AB The title compns. contain oligomers undergoing main chain degradation or hydrolysis by an acid and having alicyclic and/or conjugated polynuclear condensed aromatic structure in the main chain, and photosensitive acid generator.
IT **210712-17-7P**, Deoxycholic acid-5-(2-adamantylidene)-2,2-dimethyl-1,3-dioxane-4,6-dione copolymer
(transparent resins, photosensitive **compns.** thereof, and pattern formation using the same, with excellent transparency to long-wavelength light, dry etching resistance, and high contrast and resolution)

RN 210712-17-7 HCAPLUS
CN Cholan-24-oic acid, 3,12-dihydroxy-, (3α,5β,12α)-
, polymer with 2,2-dimethyl-5-tricyclo[3.3.1.13,7]decylidene-1,3-dioxane-4,6-dione (9CI) (CA INDEX NAME)

CM 1

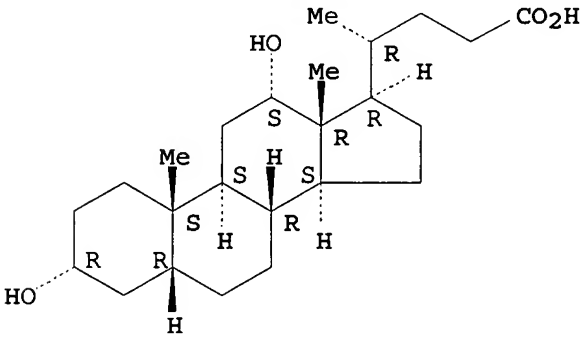
CRN 51757-47-2
CMF C16 H20 O4



CM 2

CRN 83-44-3
CMF C24 H40 O4

Absolute stereochemistry.



IC ICM G03F007-038
ICS C08G018-34; C08G063-12; C08G069-26; C08L067-00; C08L077-06; G03F007-039; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
IT 541-16-2DP, tert-Butyl malonate, reaction products with dibromoadamantane, polymers 702-98-7DP, 2-Methyl-2-adamantanol, cotrimers with adamantanedicarbonyl chloride 828-51-3DP, 1-Adamantanecarboxylic acid, codimer with adamnatanecarbonyl chloride 876-53-9DP, 1,3-Dibromoadamantane, reaction products with tert-Bu malonate, polymers 2094-72-6DP, 1-Adamantanecarbonyl chloride, codimer with adamnatanecarboxylic acid 2094-72-6DP, 1-Adamantanecarbonyl chloride, cotrimers with adamantanedicarbonyl chloride 4405-13-4P, Glyoxal trimer dihydrate 115349-14-9P 181017-30-1P, Menthyl methacrylate-tert-butyl methacrylate-methacrylic acid copolymer 210712-16-6P, trans-3,6-Endomethylene-1,2,3,6-tetrahydrophthaloyl chloride-(+)-cis-p-menthane-3,8-diol copolymer

210712-17-7P, Deoxycholic acid-5-(2-adamantylidene)-2,2-dimethyl-1,3-dioxane-4,6-dione copolymer 210712-18-8P 210712-19-9P 210712-20-2P 210712-21-3P 210712-22-4P 210712-23-5P 210712-24-6P, 4,4'-Diaminodicyclohexylmethane-1,2,3,4-cyclopentanetetracarboxylic dianhydride copolymer 210712-25-7P 210754-99-7P 210755-03-6P 210776-45-7DP, cotrimers with methyladamantanol 210776-46-8P 210776-47-9P, Adamantanedicarbonyl chloride-naphthalenedicarbonyl chloride-deoxycholic acid copolymer 210776-48-0P 210776-51-5P 210776-52-6P 210776-53-7P 210776-56-0P 210776-59-3P 210776-61-7P
(transparent resins, photosensitive **compns.** thereof, and pattern formation using the same, with excellent transparency to long-wavelength light, dry etching resistance, and high contrast and resolution)

L53 ANSWER 13 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1996:302911 HCAPLUS
DOCUMENT NUMBER: 125:45126
TITLE: Photosensitive resin composition
INVENTOR(S): Gybin, Alexander S.; Van Iseghem, Lawrence C.
PATENT ASSIGNEE(S): Chromaline Corp., USA
SOURCE: U.S., 11 pp., Division of U. S. Ser. No. 28, 420.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 5506089	A	19960409	US 1994-195258	1994 0214
US 6020436	A	20000201	US 1993-28420	1993 0309

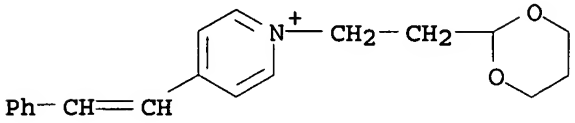
PRIORITY APPLN. INFO.: US 1993-28420 A3 1993 0309

GI For diagram(s), see printed CA Issue.
AB A universal method to make photosensitive polymers from poly(vinyl alc.) and poly(vinyl pyridine) is disclosed which generally does not require final purification and can produce photosensitive polymers which are of similar photosensitivity whether prepared with a poly(vinyl alc.) or poly(vinyl pyridine) backbone. These polymers comprise a heterocyclic, light-sensitive pendant group including a moiety having the formula I or II wherein Z1 denotes the atoms necessary to form a substituted or unsubstituted aromatic heterocyclic ring; Z2 denotes the atoms necessary to form a substituted or unsubstituted aromatic or aromatic heterocyclic ring; R is hydrogen or a substituted or unsubstituted alkyl group; Y is a residue from a grafting group that is capable of grafting the pendant group onto a polymeric backbone; n is 1 or 2.
IT **178058-96-3P 178058-97-4P 178058-99-6P**
(preparation and use in photosensitive **compns.**)
RN 178058-96-3 HCAPLUS

CN Pyridinium, 1-[2-(1,3-dioxan-2-yl)ethyl]-4-(2-phenylethenyl)-, bromide, polymer with ethenyl acetate (9CI) (CA INDEX NAME)

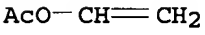
CM 1

CRN 178058-92-9
CMF C19 H22 N O2 . Br



CM 2

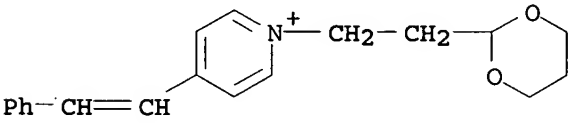
CRN 108-05-4
CMF C4 H6 O2



RN 178058-97-4 HCAPLUS
CN Pyridinium, 1-[2-(1,3-dioxan-2-yl)ethyl]-4-(2-phenylethenyl)-, bromide, polymer with ethenol (9CI) (CA INDEX NAME)

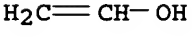
CM 1

CRN 178058-92-9
CMF C19 H22 N O2 . Br



CM 2

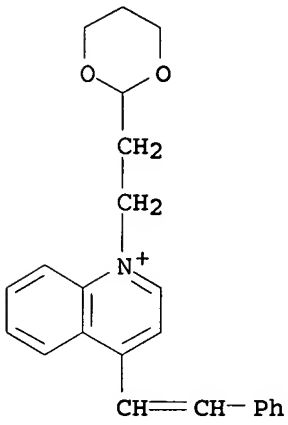
CRN 557-75-5
CMF C2 H4 O



RN 178058-99-6 HCAPLUS
CN Quinolinium, 1-[2-(1,3-dioxan-2-yl)ethyl]-4-(2-phenylethenyl)-, bromide, polymer with ethenyl acetate (9CI) (CA INDEX NAME)

CM 1

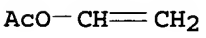
CRN 178058-98-5
CMF C23 H24 N O2 . Br



● Br^-

CM 2

CRN 108-05-4
CMF C4 H6 O2



IC ICM G03C001-73
INCL 430287000
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
IT **178058-96-3P 178058-97-4P 178058-99-6P**
178059-02-4P
(preparation and use in photosensitive **compns.**)

L53 ANSWER 14 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1995:929522 HCAPLUS
DOCUMENT NUMBER: 124:71648
TITLE: Image-forming material and method
INVENTOR(S): Hirayama, Shigeru; Watanabe, Jiro; Tsurukawa, Naoichi
PATENT ASSIGNEE(S): Toppan Printing Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent

LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 07199460	A2	19950804	JP 1993-352238	1993 1227
JP 2956463	B2	19991004		
PRIORITY APPLN. INFO.:			JP 1993-352238	1993 1227

AB The title material comprises a photosensitive layer containing a photopolymerizable compound and a photopolymn. initiator, and a colored layer containing a dye or pigment and a nonphotopolymerizable organic polymer binder. High quality simple proofs can be produced easily by using the material on printing paper.

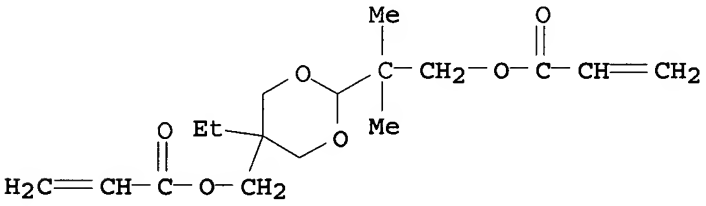
IT **172084-40-1**
(photoimaging **composition** useful for manufacture of proofs)

RN 172084-40-1 HCAPLUS

CN 2-Propenoic acid, [2-[1,1-dimethyl-2-[(1-oxo-2-propenyl)oxy]ethyl]-5-ethyl-1,3-dioxan-5-yl]methyl ester, polymer with Aronix M 7100 (9CI) (CA INDEX NAME)

CM 1

CRN 87320-05-6
CMF C17 H26 O6



CM 2

CRN 76723-57-4
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

IC ICM G03F007-004
ICS G03F007-004; G03F003-10; G03F007-027; G03F007-031; G03F007-105; G03F007-34

CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)

IT 137335-87-6 **172084-40-1**
(photoimaging **composition** useful for manufacture of proofs)

L53 ANSWER 15 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1992:642751 HCAPLUS

DOCUMENT NUMBER: 117:242751
TITLE: Photosensitive materials using silver halide development-induced polymerization
INVENTOR(S): Hirai, Hiroyuki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 24 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 04147263	A2	19920520	JP 1990-272878	1990 1011
JP 2592718	B2	19970319		
US 5192639	A	19930309	US 1991-774483	1991 1010

PRIORITY APPLN. INFO.: JP 1990-272878 A 1990 1011

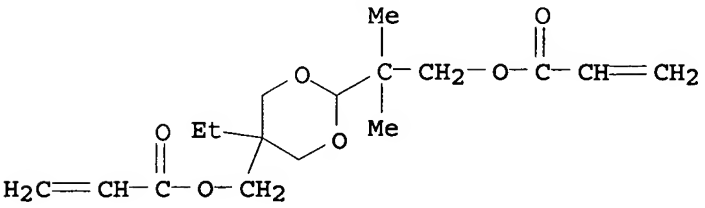
AB A photosensitive layer of the title materials is made up of microcapsules containing Ag halides, reducing agents, polymerizable compds., color image-forming substances, and bases or their precursors on a support. The photosensitive materials contain an oxide or its salt of ≥1 element selected from Cr, Mo, and W with 6 valences in the layer. The materials produce clear images at a relatively low temperature and in a short time. Thus, a support was coated with a dispersion of microcapsules containing the above constituents and K2CrO4 to give a photosensitive sheet.

IT **116321-27-8**
(photoimaging polymerization-type **composition** containing, with silver halide)

RN 116321-27-8 HCAPLUS
CN 2-Propenoic acid, [2-[1,1-dimethyl-2-[(1-oxo-2-propenyl)oxy]ethyl]-5-ethyl-1,3-dioxan-5-yl]methyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 87320-05-6
CMF C17 H26 O6



IC ICM G03F007-004
ICS G03F007-06

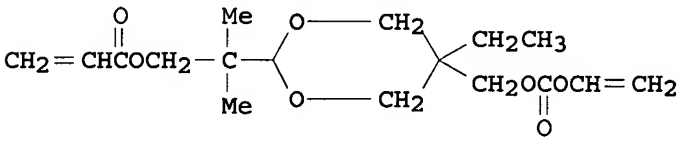
CC 74-4 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
IT 71512-49-7 90216-38-9 **116321-27-8** 136168-28-0
(photoimaging polymerization-type **composition** containing, with silver halide)

L53 ANSWER 16 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1990:641566 HCAPLUS
DOCUMENT NUMBER: 113:241566
TITLE: Optical recording material
INVENTOR(S): Tachibana, Shinichi
PATENT ASSIGNEE(S): Canon K. K., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 02078034	A2	19900319	JP 1988-228476	19880914

PRIORITY APPLN. INFO.: JP 1988-228476 19880914

GI

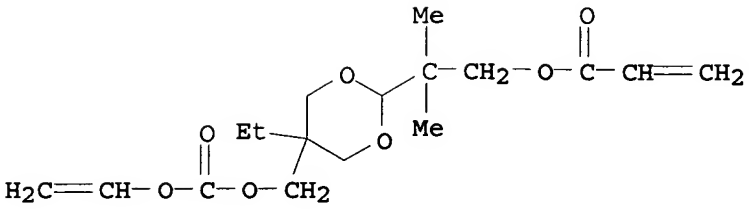


I

AB An optical recording material, which is a hardened resin layer provided with preformat signals and tracking grooves coated on a transparent disk, is obtained by using a UV-hardenable resin composition containing as a prepolymer component a carbonate diol diarylate (average mol. weight 500-5000), I (as an acrylate component), and a photopolymn. initiator.
IT **130725-09-6 130726-44-2 130726-45-3 130743-50-9**
(UV-curable **compns.** containing, for optical recording material preparation)
RN 130725-09-6 HCAPLUS
CN 2-Propenoic acid, 2-[5-[[[(ethenyloxy)carbonyl]oxy]methyl]-5-ethyl-1,3-dioxan-2-yl]-2-methylpropyl ester, polymer with DN 983 2-propenoate and 2-[3a,4,5,6,7,7a-hexahydro-4,7-methano-1H-inden-5(or 6)-yl]ethyl 2-propenoate (9CI) (CA INDEX NAME)

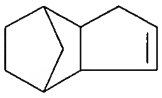
CM 1

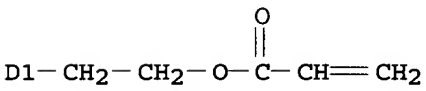
CRN 130725-07-4
CMF C17 H26 O7



CM 2

CRN 83784-39-8
CMF C15 H20 O2
CCI IDS





CM 3

CRN 130589-17-2
CMF C3 H4 O2 . x Unspecified

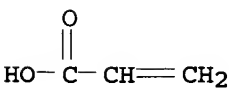
CM 4

CRN 130939-35-4
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 5

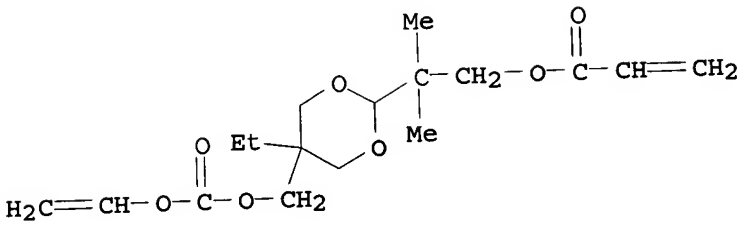
CRN 79-10-7
CMF C3 H4 O2



RN 130726-44-2 HCAPLUS
CN 2-Propenoic acid, 2-[5-[[[(ethenyloxy)carbonyl]oxy]methyl]-5-ethyl-1,3-dioxan-2-yl]-2-methylpropyl ester, polymer with Nippollan 983 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 130725-07-4
CMF C17 H26 O7



CM 2

CRN 130589-17-2
CMF C3 H4 O2 . x Unspecified

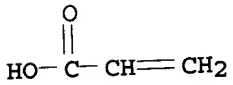
CM 3

CRN 130939-35-4
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 4

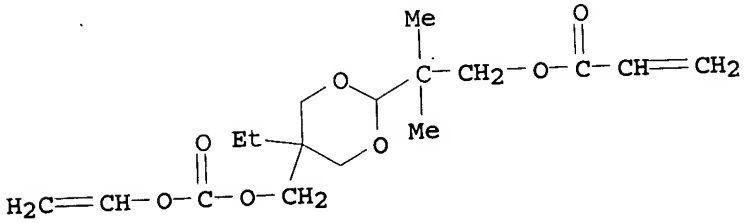
CRN 79-10-7
CMF C3 H4 O2



RN 130726-45-3 HCAPLUS
CN 2-Propenoic acid, 2-[5-[[[(ethenyloxy)carbonyl]oxy]methyl]-5-ethyl-1,3-dioxan-2-yl]-2-methylpropyl ester, polymer with Nippollan 982 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 130725-07-4
CMF C17 H26 O7



CM 2

CRN 130589-16-1
CMF C3 H4 O2 . x Unspecified

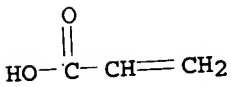
CM 3

CRN 115803-95-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 4

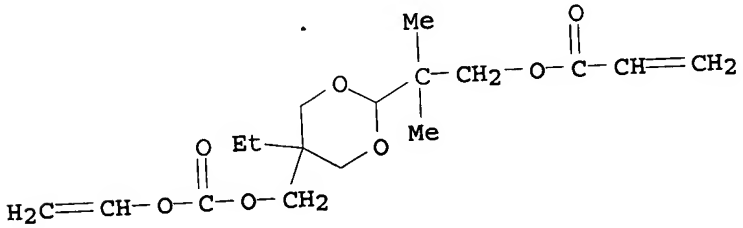
CRN 79-10-7
CMF C3 H4 O2



RN 130743-50-9 HCAPLUS
CN 2-Propenoic acid, 2-[5-[[[(ethenyloxy)carbonyl]oxy]methyl]-5-ethyl-1,3-dioxan-2-yl]-2-methylpropyl ester, polymer with 2-[3a,4,5,6,7,7a-hexahydro-4,7-methano-1H-inden-5(or 6)-yl]ethyl 2-propenoate and Nippollan 982 propenoate (9CI) (CA INDEX NAME)

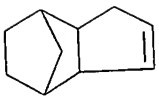
CM 1

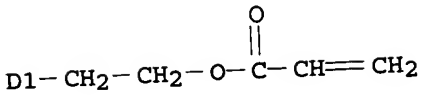
CRN 130725-07-4
CMF C17 H26 O7



CM 2

CRN 83784-39-8
CMF C15 H20 O2
CCI IDS





CM 3

CRN 130589-16-1
CMF C3 H4 O2 . x Unspecified

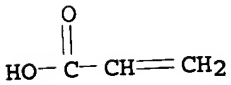
CM 4

CRN 115803-95-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 5

CRN 79-10-7
CMF C3 H4 O2



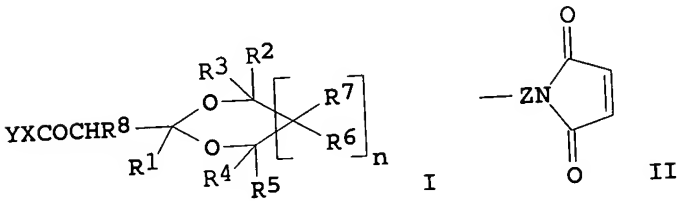
IC ICM G11B007-24
ICS C08F002-48
ICA B32B027-30; C08J007-04
CC 74-12 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
IT **130725-09-6 130726-44-2 130726-45-3 130743-50-9**
(UV-curable **compns.** containing, for optical recording material preparation)

L53 ANSWER 17 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1990:506442 HCAPLUS
DOCUMENT NUMBER: 113:106442
TITLE: Unsaturated β-keto ester acetals and their use in photoimaging compositions
INVENTOR(S): Schulthess, Adrian; Hunziker, Max
PATENT ASSIGNEE(S): Ciba-Geigy A.-G., Switz.
SOURCE: Eur. Pat. Appl., 34 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 347381	A1	19891220	EP 1989-810430	1989 0607
EP 347381	B1	19920212		
R: BE, CH, DE, ES, FR, GB, IT, LI, NL, SE				
US 5059698	A	19911022	US 1989-363801	1989 0609
CA 1337771	A1	19951219	CA 1989-602272	1989 0609
JP 02051509	A2	19900221	JP 1989-150333	1989 0613
PRIORITY APPLN. INFO.:			CH 1988-2257 A	1988 0613

OTHER SOURCE(S): MARPAT 113:106442

GI



I II

AB The title compds. I or YXCOCHR8CR1OR12OR13 [n = 0-2; R1 = H, alkyl, Ph, benzyl, etc.; R2-R8 = H, halogen, alkyl, Ph, naphthyl, CO2R9, -p-C6H4CO2R9, SO2R9 (R9 = alkyl, Ph); X = O, S, NR10 (R10 = H, R9); Y = CR11:CH2, -p-C6H4-CR11:CH2, ZOCR11:CH2, II, ZOCOCR11:CH2, ZNR11COCR11:CH2, ZO2CCH:CHCO2R11, ZNR11CH2COCH:CHCO2R11 (R11 = R10; Z = ≥2 methylene group-containing residue; R12, R13 = R9, naphthyl)] are prepared for use in photoimaging compns. for photoresists, integrated circuit manufacturing, printing plates, ans the like.

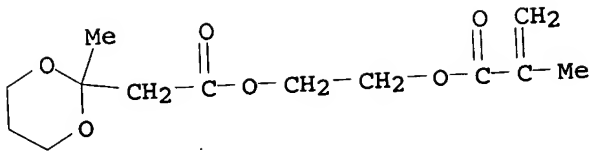
IT **128692-56-8P 128692-58-0P**
(preparation of, for photoimaging **compns.**)

RN 128692-56-8 HCAPLUS

CN 1,3-Dioxane-2-acetic acid, 2-methyl-, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with [(2-methyl-1-oxo-2-propenyl)oxy]methyl 3-oxobutanoate (9CI) (CA INDEX NAME)

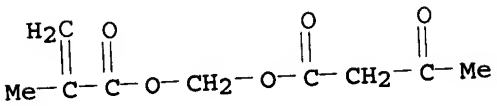
CM 1

CRN 128692-57-9
CMF C13 H20 O6



CM 2

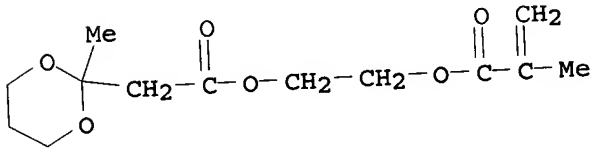
CRN 122458-42-8
CMF C9 H12 O5



RN 128692-58-0 HCAPLUS
CN 1,3-Dioxane-2-acetic acid, 2-methyl-, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 128692-57-9
CMF C13 H20 O6



IC ICM C07D317-30
ICS C07D319-06; C07C069-66; C08F020-18; G03F007-10
CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 28, 76
IT 128692-53-5P **128692-56-8P 128692-58-0P**
128692-59-1P 128692-61-5P 128692-63-7P 128692-65-9P
(preparation of, for photoimaging **compns.**)

L53 ANSWER 18 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1985:87671 HCAPLUS
DOCUMENT NUMBER: 102:87671
TITLE: Photocrosslinkable compositions
PATENT ASSIGNEE(S): Ricoh Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 59058427	A2	19840404	JP 1982-169203	1982 0928

PRIORITY APPLN. INFO.: JP 1982-169203 1982 0928

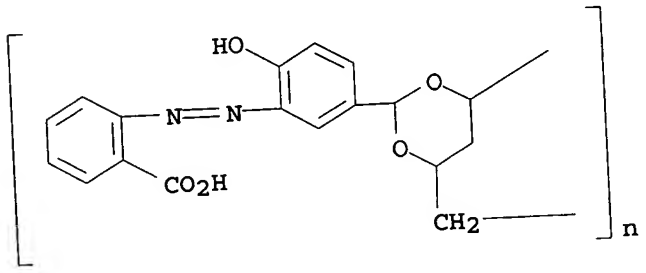
GI

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

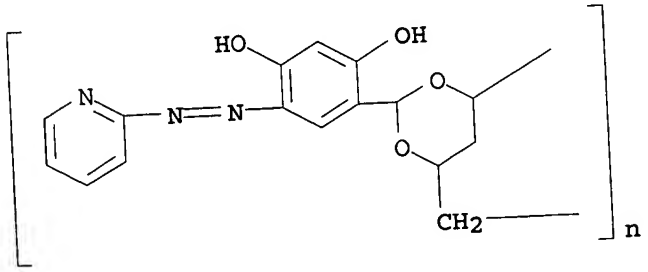
AB Photocrosslinkable compns. for printing plate preparation contain a Co(III) complex, a photoreducing agent, a H donor, and a chelating macromol. ligand having the repeating unit I (R = H, Me, OH, OMe, OEt; R1 = II, VI, VII, VIII, IX, X; R2, R3 = H, Me, OH, OMe, OEt, CO2H, SO3H, N(Me)2, III, IV, V, NO, NO3, Cl, Br). Thus, a chelating macromol. ligand having the repeating unit XI 100, hexamminecobalt(III) trifluoroacetate 150, 9,10-phenanthrenequinone 30, and polyethylene glycol 50 mg were dissolved in MeCOEt 10 mL, coated on an Al sheet, and dried to give a photosensitive plate useful for making a printing plate.

IT **94797-91-8 94797-92-9 94797-93-0**
94797-94-1 94797-95-2
(photocrosslinkable **compns.** containing, for printing plate preparation)

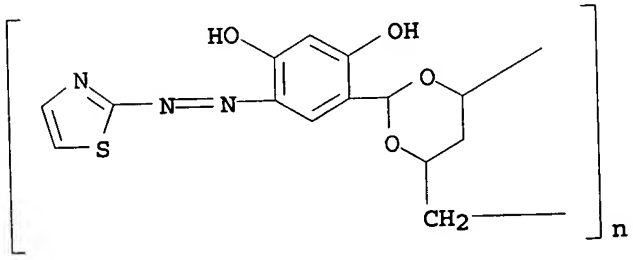
RN 94797-91-8 HCAPLUS
CN Poly[[2-[3-[(2-carboxyphenyl)azo]-4-hydroxyphenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)



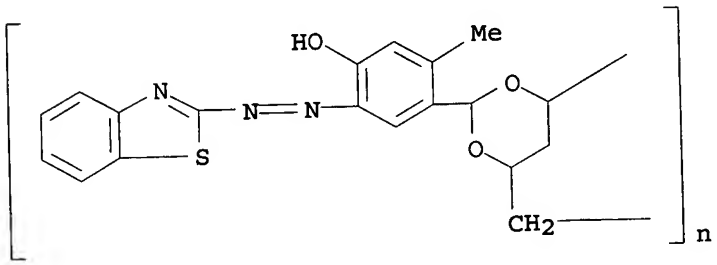
RN 94797-92-9 HCAPLUS
CN Poly[[2-[2,4-dihydroxy-5-(2-pyridinylazo)phenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)



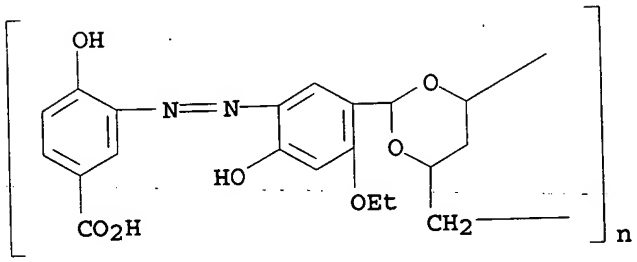
RN 94797-93-0 HCAPLUS
CN Poly[[2-[2,4-dihydroxy-5-(2-thiazolylazo)phenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)



RN 94797-94-1 HCAPLUS
CN Poly[[2-[5-(2-benzothiazolylazo)-4-hydroxy-2-methylphenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)



RN 94797-95-2 HCAPLUS
CN Poly[[2-[5-[(5-carboxy-2-hydroxyphenyl)azo]-2-ethoxy-4-hydroxyphenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)



IC G03C001-71; C08F008-30; C08L029-14
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
IT 84-11-7 25322-68-3 59561-55-6 **94797-91-8** **94797-92-9** **94797-93-0** **94797-94-1** **94797-95-2**
(photocrosslinkable **compns.** containing, for printing plate preparation)

L53 ANSWER 19 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1981:471073 HCAPLUS
DOCUMENT NUMBER: 95:71073
TITLE: Photosensitive mixture for relief images
INVENTOR(S): Buhr, Gerhard; Ruckert, Hans
PATENT ASSIGNEE(S): Hoechst A.-G., Fed. Rep. Ger.
SOURCE: Eur. Pat. Appl., 47 pp.
CODEN: EPXXDW

DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

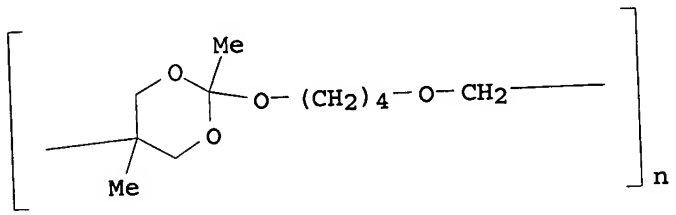
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 22571	A1	19810121	EP 1980-104006	1980 0711
EP 22571	B1	19821222		
R: AT, BE, CH, DE, FR, GB, IT, NL, SE				
DE 2928636	A1	19810212	DE 1979-2928636	1979 0716
CA 1133743	A1	19821019	CA 1980-355539	1980 0704
AU 8060152	A1	19810122	AU 1980-60152	1980 0707
AU 533172	B2	19831103		
AT 2099	E	19830115	AT 1980-104006	1980 0711
BR 8004395	A	19810127	BR 1980-4395	1980 0715
ZA 8004267	A	19810729	ZA 1980-4267	1980 0715
US 4311782	A	19820119	US 1980-169133	1980 0715
JP 56017345	A2	19810219	JP 1980-96290	1980 0716
JP 63020325	B4	19880427		
PRIORITY APPLN. INFO.:			DE 1979-2928636 A	1979 0716
			EP 1980-104006 A	1980 0711

AB Radiation-sensitive pos.-working compns. for the production of relief images are comprised of an acid-forming compound and a polymeric compound with recurring orthocarbonic acid ester groups in the main chain and whose solubility in a liquid developer is increased by the presence of an acid. Thus, a polymeric orthoester was prepared by mixing 1,2,6-hexanetriol 23.65, tri-Me orthoformate 22.5 g, and

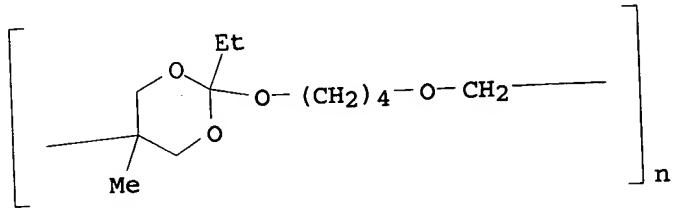
p-toluenesulfonic acid 25 mg, distilling off MeOH over 5 h, heating to 160°, adding Et2O 50 mL, stirring with K2CO3, filtering, and removing the solvent under reduced pressure. This polymeric orthoester 1.2, a cresol-HCHO resin 4.0, 2-acenaphth-5-yl-4,6-bis(trichloromethyl)-s-triazine 0.2, and MeCOEt 94.6 parts were mixed, coated on a grained Al plate, exposed with a Leitz Prado projector at 65 cm and developed in an alkaline solution to give a pos. copy of a black-and-white line image capable of being used as an offset printing plate.

IT **78538-26-8 78538-27-9 78538-28-0**
78538-29-1 78538-30-4 78538-31-5
78538-32-6 78538-33-7 78538-34-8
78538-35-9 78538-36-0 78538-37-1
78538-38-2 78538-39-3 78538-40-6
(radiation-sensitive resist **compns.** containing, pos.-working)

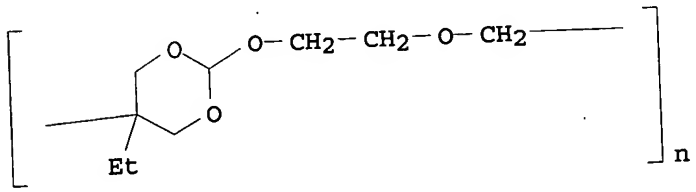
RN 78538-26-8 HCAPLUS
CN Poly[(2,5-dimethyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediyloxymethylene] (9CI) (CA INDEX NAME)



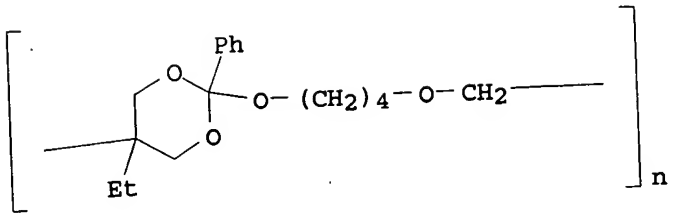
RN 78538-27-9 HCAPLUS
CN Poly[(2-ethyl-5-methyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediyloxymethylene] (9CI) (CA INDEX NAME)



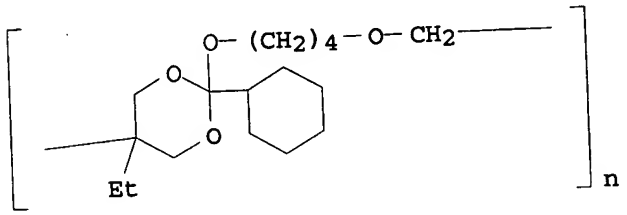
RN 78538-28-0 HCAPLUS
CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,2-ethanediyloxymethylene] (9CI) (CA INDEX NAME)



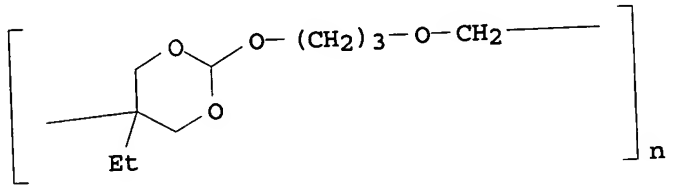
RN 78538-29-1 HCAPLUS
CN Poly[(5-ethyl-2-phenyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediyloxymethylene] (9CI) (CA INDEX NAME)



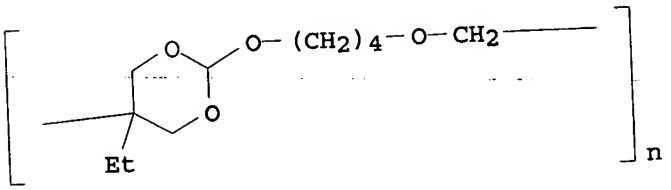
RN 78538-30-4 HCAPLUS
CN Poly[(2-cyclohexyl-5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediyloxymethylene] (9CI) (CA INDEX NAME)



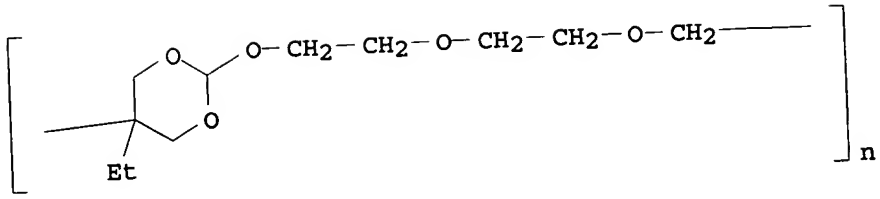
RN 78538-31-5 HCAPLUS
CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,3-propanediyloxymethylene] (9CI) (CA INDEX NAME)



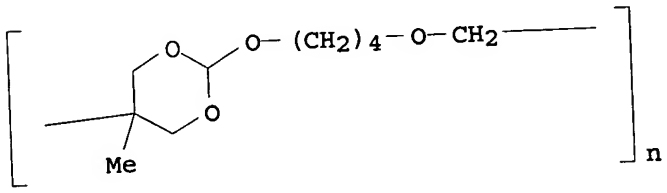
RN 78538-32-6 HCAPLUS
CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediyloxymethylene] (9CI) (CA INDEX NAME)



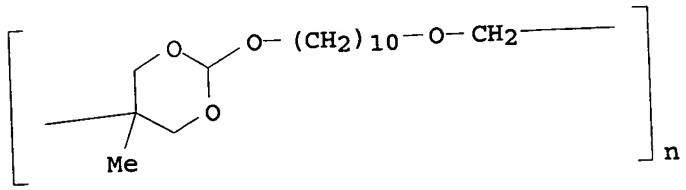
RN 78538-33-7 HCAPLUS
CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,2-ethanediyloxy-1,2-ethanediyloxymethylene] (9CI) (CA INDEX NAME)



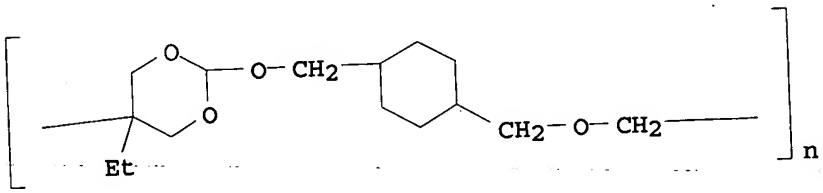
RN 78538-34-8 HCAPLUS
CN Poly[(5-methyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediyloxymethylene] (9CI) (CA INDEX NAME)



RN 78538-35-9 HCAPLUS
CN Poly[(5-methyl-1,3-dioxane-5,2-diyl)oxy-1,10-decanediyloxymethylene] (9CI) (CA INDEX NAME)

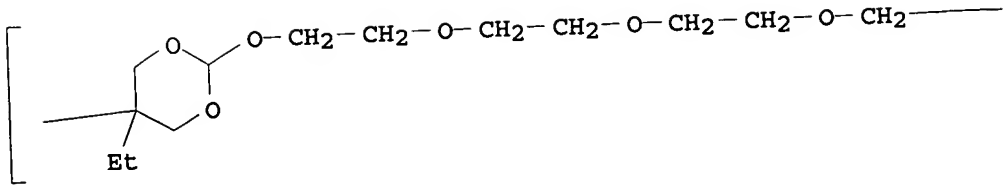


RN 78538-36-0 HCAPLUS
CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxymethylene-1,4-cyclohexanediylmethyleneoxymethylene] (9CI) (CA INDEX NAME)



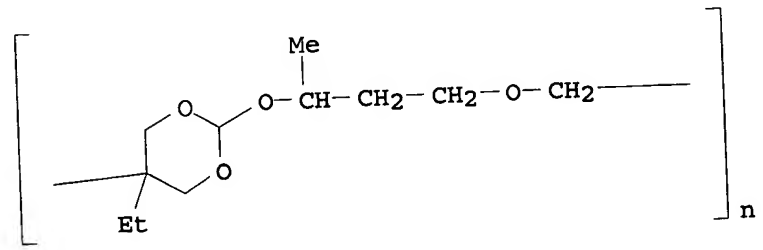
RN 78538-37-1 HCAPLUS
CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,2-ethanediyloxy-1,2-ethanediyloxy-1,2-ethanediyloxymethylene] (9CI) (CA INDEX NAME)

PAGE 1-A

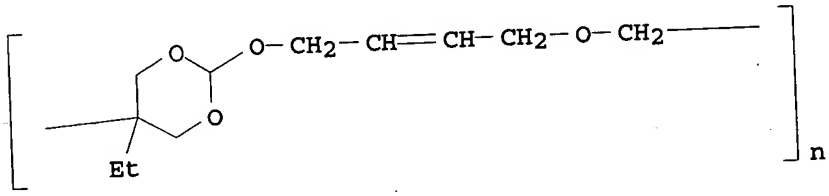


PAGE 1-B

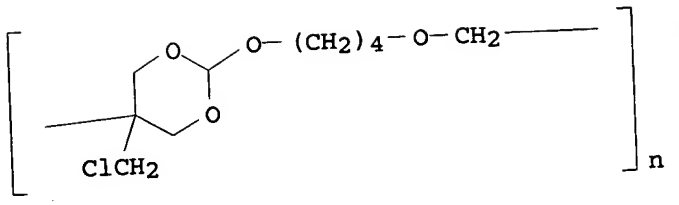
RN 78538-38-2 HCAPLUS
CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy(1-methyl-1,3-propanediyl)oxymethylene] (9CI) (CA INDEX NAME)



RN 78538-39-3 HCAPLUS
CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-2-butene-1,4-diyloxymethylene] (9CI) (CA INDEX NAME)



RN 78538-40-6 HCAPLUS
CN Poly[[5-(chloromethyl)-1,3-dioxane-5,2-diyl]oxy-1,4-butanediyloxymethylene] (9CI) (CA INDEX NAME)

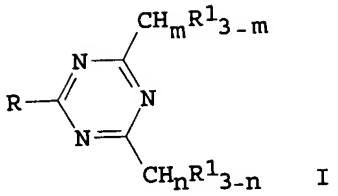


IC G03C001-72
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** Processes)
IT **Lithographic** plates
Printing plates
(photosensitive compns. containing polymeric orthoesters for)
IT 467-63-0 6542-67-2 9016-83-5 36451-09-9 38686-70-3
41749-18-2 42573-57-9 64524-15-8 69432-40-2 69432-41-3
69432-57-1 78537-86-7 **78538-26-8 78538-27-9**
78538-28-0 78538-29-1 78538-30-4
78538-31-5 78538-32-6 78538-33-7
78538-34-8 78538-35-9 78538-36-0
78538-37-1 78538-38-2 78538-39-3
78538-40-6
(radiation-sensitive resist **compns.** containing, pos.-working)

L53 ANSWER 20 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1980:485223 HCAPLUS
DOCUMENT NUMBER: 93:85223
TITLE: Radiation-sensitive copying composition
INVENTOR(S): Buhr, Gerhard
PATENT ASSIGNEE(S): Hoechst A.-G., Fed. Rep. Ger.
SOURCE: U.S., 9 pp.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 4189323	A	19800219	US 1978-899272	1978 0424
DE 2718259	A1	19781102	DE 1977-2718259	1977 0425
DE 2718259	C2	19821125		
PRIORITY APPLN. INFO.:			DE 1977-2718259 A	1977 0425

GI



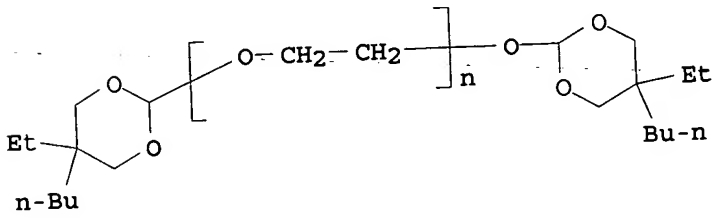
I

AB Radiation-sensitive copying compns. for use in preparing printing plates, color proofing films, resists, and the like are composed of an ethylenically unsatd. compound capable of undergoing a polymerization reaction initiated by free radicals or a compound capable of undergoing a cationic polymerization under the action of acid catalysts and an s-triazine of formula I (R = a substituted or unsubstituted bi- or polynuclear aromatic or heterocyclic aromatic group which can be partially hydrogenated and is linked by an unsatd. nuclear C atom; R1 = Br or Cl; m, n = 0-3; and m + n = <5). Thus, an electrolytically roughened and anodized Al plate was whirl-coated with a coating solution containing trimethylolethane triacrylate 6.7, methacrylic acid-Me methacrylate copolymer (acid no 115) 6.5, I (R = 4-ethoxy-1-naphthyl; R1 = Cl; m,n = 0) 0.12, ethylene glycol monoethyl ether 64.0, BuOAc 22.7, and 2,4-dinitro-6-chloro-2'-acetamido-5'-methoxy-4'-(β-hydroxyethyl-β'-cyanoethyl)aminoazobenzene 0.3 parts by weight to give a 3-4 g/m2 dry layer. After providing the plate with a 4 μm thick protective layer of poly(vinyl alc.), the layer was exposed for 30 s at 110 cm to a 5 kW metal halide lamp under a line/screen original, and developed with 1.5% aqueous Na metasilicate to give a neg. of the original that when used in an offset press produced 200,000 copies of good quality.

IT **74217-21-3**
(radiation-sensitive **compns.** containing triazine derivs. and, for photoresists, color proofing films, and printing plates)

RN 74217-21-3 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-(5-butyl-5-ethyl-1,3-dioxan-2-yl)-ω-[(5-butyl-5-ethyl-1,3-dioxan-2-yl)oxy]- (9CI) (CA INDEX NAME)



IC G03C001-68

INCL 430281000

CC 74-5 (Radiation Chemistry, Photochemistry, and **Photographic** Processes)

IT 109-16-0 548-62-9 1484-13-5 1628-58-6 9003-35-4 9016-83-5 19778-85-9 23807-28-5 24687-64-7 25068-38-6 25086-15-1 41137-60-4 58601-54-0 64502-14-3 69418-08-2 69666-21-3 **74217-21-3** 74217-60-0

(radiation-sensitive compns. containing triazine derivs. and, for photoresists, color proofing films, and printing plates)

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